

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: BETELHEM SHEWAREGED Examiner #: 75633 Date: 04/07/2005
 Art Unit: 1774 Phone Number 30 2-1529 Serial Number: 101613,497
 Mail Box and Bldg/Room Location: REM 9D21 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Ink jet recording materials containing Siloxane copolymer ^{Surfactant}
 Inventors (please provide full names): Tienteh Chen SCIENTIFIC REFERENCE BP
 Sci & Tech Inf. Ctr

Earliest Priority Filing Date: 07/02/2003 APR 8 REC'D

For Sequence Searches Only Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number. Pat. & T.M. Office

1. Ink jet recording medium containing a nonionic siloxane copolymer surfactant having a structural formula received in claim 2.
2. Ink jet recording medium containing a nonionic siloxane copolymer surfactant having a structural formula received in claim 3.

STAFF USE ONLY		Type of Search	Vendors and cost where applicable
Searcher: <u>Whe</u>	NA Sequence (#)	STN	<u>84 523.04</u>
Searcher Phone #:	AA Sequence (#)	Dialog	
Searcher Location:	Structure (#)	Questel/Orbit	
Date Searcher Picked Up: <u>4/20/05</u>	Bibliographic	Dr. Link	
Date Completed: <u>4/21/05</u>	Litigation	Lexis/Nexis	
Searcher Prep & Review Time: <u>120</u>	Fulltext	Sequence Systems	
Clerical Prep Time: <u>30</u>	Patent Family	WWW/Internet	
Online Time: <u>120</u>	Other	Other (specify)	



STIC Search Report

EIC 1700

STIC Database Tracking Number: 10613497

TO: Betelhem Shewareged
Location: REM 9D21
Art Unit: 1774 10613497
April 21, 2005

Case Serial Number: 10/613497

From: Usha Shrestha
Location: EIC 1700
REMSEN 4B28
Phone: 571/272-3519
usha.shrestha@uspto.gov

Search Notes



STIC Search Results Feedback Form

EIC17000

Questions about the scope or the results of the search? Contact **the EIC searcher or contact:**

Kathleen Fuller, EIC 1700 Team Leader
571/272-2505 REMSEN 4B28

Voluntary Results Feedback Form

➤ *I am an examiner in Workgroup:* *Example: 1713*

➤ *Relevant prior art found, search results used as follows:*

- 102 rejection
- 103 rejection
- Cited as being of interest.
- Helped examiner better understand the invention.
- Helped examiner better understand the state of the art in their technology.

Types of relevant prior art found:

- Foreign Patent(s)
- Non-Patent Literature
(journal articles, conference proceedings, new product announcements etc.)

➤ *Relevant prior art not found:*

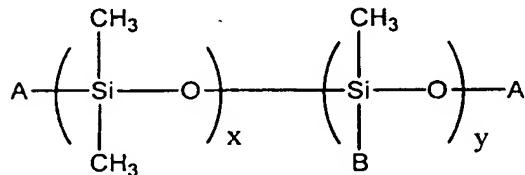
- Results verified the lack of relevant prior art (helped determine patentability).
- Results were not useful in determining patentability or understanding the invention.

Comments:

CLAIMS

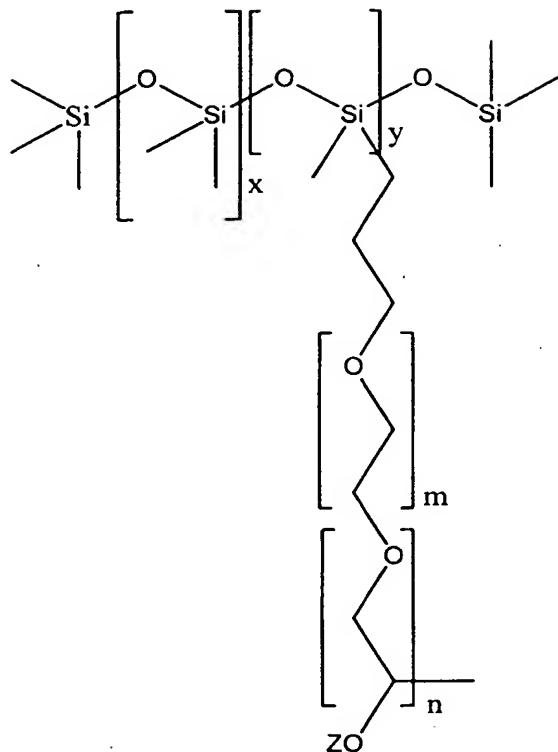
5 1. A print medium comprising an ink-receiving layer and a coated paperbase, the ink-receiving layer comprising a nonionic siloxane copolymer surfactant.

10 2. The print medium of claim 1, wherein the nonionic siloxane copolymer surfactant comprises the following structure:



wherein A is $-\text{CH}_3$ or B, and B is a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and x and y are such as to provide a molecular weight greater than about 1000.

15 3. The print medium of claim 1, wherein the nonionic siloxane copolymer surfactant comprises the following structure:



wherein m, n, x, and y are such as to provide a molecular weight greater than about 1000, wherein Z is H, $-\text{CH}_3$, or a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and wherein the structure contains at least one polyethyleneoxide group.

4. The print medium of claim 1, wherein the surface tension of the nonionic siloxane copolymer surfactant is from about 20 dyne/cm to about 35 dyne/cm.

10

5. The print medium of claim 1, wherein the hydrophilic/hydrophobic balance value (HLB) of the nonionic siloxane copolymer surfactant is from about 10 to about 30.

15

6. The print medium of claim 1, wherein the weight percent (wt %) of the nonionic siloxane copolymer surfactant is from about 0.05 wt % to about 2 wt %.

7. The print medium of claim 1, wherein the nonionic siloxane copolymer surfactant has a molecular weight of greater than about 1000.

8. The print medium of claim 1, wherein the ink-receiving layer 5 further comprises a nonionic or anionic surfactant, wherein the nonionic or anionic surfactant is present in a concentration that is less than the concentration of the nonionic siloxane copolymer surfactant present in the ink-receiving layer.

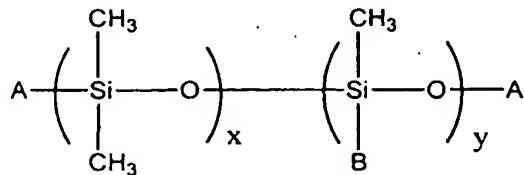
10 9. The print medium of claim 1, wherein the nonionic siloxane copolymer surfactant comprises at least one polysiloxane-polyethylene oxide compound or at least one polysiloxane-polyethylene oxide-polypropylene oxide compound.

15 10. The print medium of claim 1, wherein the coated paperbase comprises a coated paper, a cast-coated paper, or a commercial offset paper.

11. A method of forming a print medium having improved image quality and permanence, comprising:

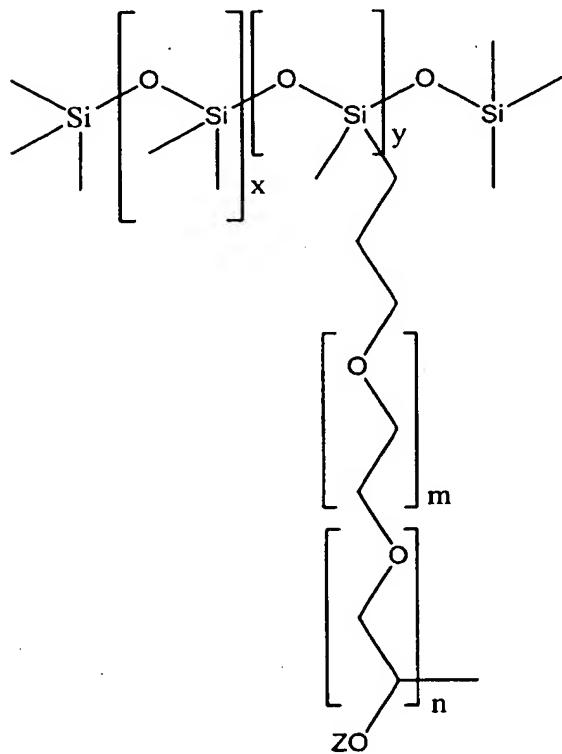
20 providing a coated paperbase; and applying an ink-receiving layer to the coated paperbase, the ink-receiving layer comprising a nonionic siloxane copolymer surfactant.

12. The method of claim 11, wherein applying an ink-receiving layer to 25 the coated paperbase comprises applying a surfactant having the following structure:



wherein A is $-\text{CH}_3$ or B, and B is a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and x and y are such as to provide a molecular weight greater than about 1000.

5 13. The method of claim 11, wherein applying an ink-receiving layer to the coated paperbase comprises applying a surfactant having the following structure:



10 wherein m, n, x, and y are such as to provide a molecular weight greater than about 1000, wherein Z is H, $-\text{CH}_3$, or a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and wherein the structure contains at least one polyethylenoxide group.

15 14. The method of claim 11, wherein applying an ink-receiving layer to the coated paperbase comprises applying a nonionic siloxane copolymer surfactant having a molecular weight of greater than about 1000.

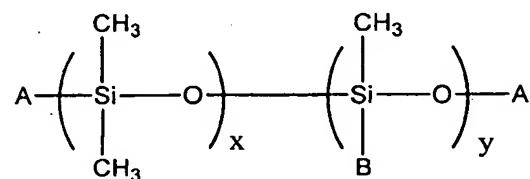
15. The method of claim 11, wherein applying an ink-receiving layer to the coated paperbase comprises applying a nonionic siloxane copolymer surfactant having at least one polysiloxane-polyethylene oxide compound or at least one polysiloxane-polyethylene oxide-polypropylene oxide compound.

5

16. A method of printing an image having improved image quality and permanence, comprising:

providing a print medium comprising a coated paperbase and an ink-receiving layer present on the coated paperbase, the ink-receiving layer comprising a nonionic siloxane copolymer surfactant; and
10 printing the image on the print medium.

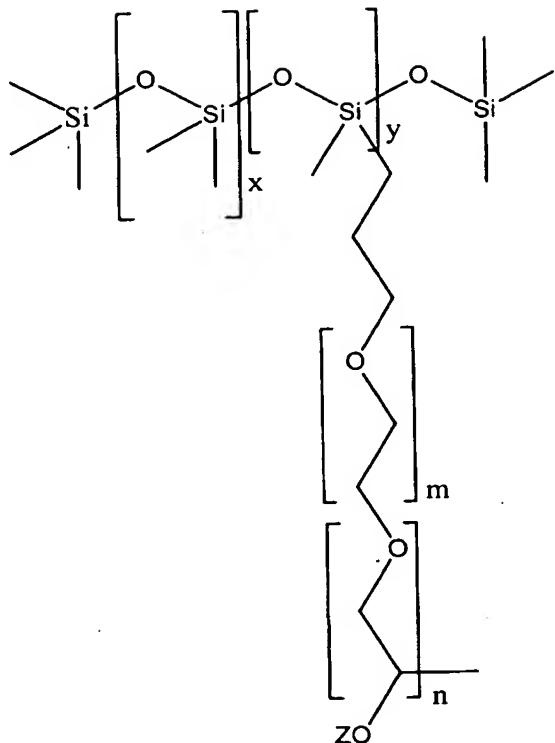
17. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having a surfactant with the following structure:



wherein A is $-\text{CH}_3$ or B, and B is a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and x and y are such as to provide a molecular weight greater than about 1000.

20

18. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having a surfactant with the following structure:



wherein m, n, x, and y are such as to provide a molecular weight greater than about 1000, wherein Z is H, $-\text{CH}_3$, or a C_1 to C_{10} straight chain or branched primary or secondary hydroxy terminated alkylene group, and wherein the structure contains at least one polyethyleneoxide group.

19. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having a nonionic siloxane copolymer surfactant with a molecular weight of greater than about 1000.

10 20. The method of claim 16, wherein providing a print medium comprises providing an ink-receiving layer having at least one polysiloxane-polyethylene oxide compound or at least one polysiloxane-polyethylene oxide-polypropylene oxide compound.

=> fil reg

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FILE 'HCAPLUS' ENTERED AT 09:24:24 ON 21 APR 2005
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 SEL RN

FILE 'REGISTRY' ENTERED AT 09:24:53 ON 21 APR 2005
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 OR 441052-10-4/BI OR 51569-39-2/BI OR 587848-36-0/BI
 OR 691397-13-4/BI OR 9002-93-1/BI OR 9005-64-5/BI OR
 9005-66-7/BI OR 9014-85-1/BI)
 D L2
 D L2 1-10 RN STR
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 D SCAN
 L4 1 SEA ABB=ON PLU=ON 9005-66-7/RN
 D SCAN
 L5 2 SEA ABB=ON PLU=ON L2 AND SILWET
 D L5 1-2 RN STR
 L6 1 SEA ABB=ON PLU=ON 587848-36-0/RN
 D SCAN
 L7 STR
 L8 STR
 L9 STR
 L10 SCR 2043
 L11 50 SEA SSS SAM L7 AND L8 AND L9 AND L10
 D QUE STAT L11
 L12 1429 SEA SSS FUL L7 AND L8 AND L9 AND L10
 SAV L12 SHE497/A

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 L14 625 SEA ABB=ON PLU=ON L13 (L) TEM?/RL
 L15 190 SEA ABB=ON PLU=ON L13 AND PHOTO?/SC, SX
 D FHITSTR
 L16 7 SEA ABB=ON PLU=ON L15 AND INK? (A) JET?
 L17 12 SEA ABB=ON PLU=ON L15 AND INK?
 D FHITSTR
 L18 12 SEA ABB=ON PLU=ON L16 OR L17
 L19 120594 SEA ABB=ON PLU=ON (POLYSILOXANE? OR SILWET? OR

SILOXANE?) / IT
 L20 398 SEA ABB=ON PLU=ON L19 AND (DI-ME OR DIMETHYL?) AND
 POLYETHYLENE (A) POLYPROPYLENE (A) GLYCOL?
 L21 197 SEA ABB=ON PLU=ON L20 AND POLYOXYALKYLEN?
 L22 9 SEA ABB=ON PLU=ON L21 AND PHOTO?/SC
 L23 9 SEA ABB=ON PLU=ON L21 AND PHOTO?/SC, SX
 L24 14 SEA ABB=ON PLU=ON L21 AND INK?
 D SCAN TI
 L25 5 SEA ABB=ON PLU=ON L21 AND RECORD?
 L26 22 SEA ABB=ON PLU=ON L23 OR L24 OR L25
 L27 21 SEA ABB=ON PLU=ON L15 AND RECORD?
 L28 26 SEA ABB=ON PLU=ON L18 OR L27
 L29 48 SEA ABB=ON PLU=ON L26 OR L28
 L30 120466 SEA ABB=ON PLU=ON (POLYSILOXANE? OR SILOXANE?) / IT
 L31 398 SEA ABB=ON PLU=ON L30 AND (DI-ME OR DIMETHYL? OR
 DI (A) METHYL) AND
 POLYETHYLENE (A) POLYPROPYLENE (A) GLYCOL?
 L32 197 SEA ABB=ON PLU=ON L31 AND POLYOXYALKYLEN?
 L33 9 SEA ABB=ON PLU=ON L32 AND PHOTO?/SC, SX
 L34 5 SEA ABB=ON PLU=ON L32 AND RECORD?
 L35 12 SEA ABB=ON PLU=ON L33 OR L34
 L36 1 SEA ABB=ON PLU=ON L35 AND L1
 L37 38 SEA ABB=ON PLU=ON L28 OR L35

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FILE HCPLUS

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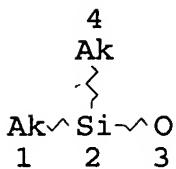
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L7 STR



NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

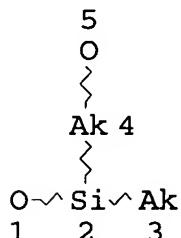
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NUMBER OF NODES IS 4

STEREO ATTRIBUTES: NONE

L8 STR



NODE ATTRIBUTES:

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DEFAULT ECLEVEL IS LIMITED

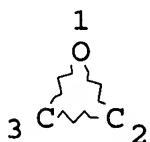
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NUMBER OF NODES IS 5

STEREO ATTRIBUTES: NONE

L9 STR



NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 3

STEREO ATTRIBUTES: NONE

L10 SCR 2043
 L12 1429 SEA FILE=REGISTRY SSS FUL L7 AND L8 AND L9 AND L10
 L13 1218 SEA FILE=HCAPLUS ABB=ON PLU=ON L12

=> fil hcap

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=> d 137 1-38 ibib abs hitstr hitind

L37 ANSWER 1 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2005:259285 HCAPLUS
 DOCUMENT NUMBER: 142:325989
 TITLE: Ink-jet recording
 head and ink-jet
 recording device
 INVENTOR(S): Kato, Eiichi; Ishizuka, Takahiro
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: U.S. Pat. Appl. Publ., 50 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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US 2005062801	A1	20050324	US 2004-946296
2004			
0922			
JP 2005096214	A2	20050414	JP 2003-332240

2003

0924

PRIORITY APPLN. INFO.:

JP 2003-332240

A

2003

0924

AB To provide an **ink jet recording** head in which a high **ink** repelling property is kept even against the repeated use and which is excellent in film strength and abrasion resistance and is excellent with respect to printing quality of the resulting image, the **ink-jet recording** head comprises a nozzle having: a hole for discharging a **recording** liquid including an **ink**; and a portion capable of repelling the **ink** at the periphery of the hole, wherein the portion comprises a cured film formed from a composition comprising a block copolymer, and the block

copolymer comprises: a block polymer comprising a fluorine-containing polymer; and a block polymer comprising a repeating unit having a siloxane structure.

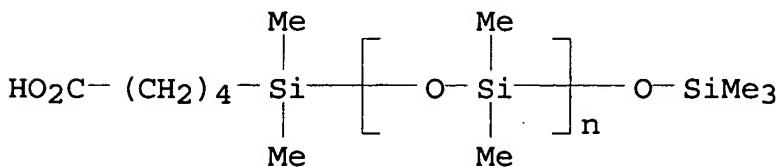
IT 848229-99-2DP, trimethylsilyl ether 848366-82-5P
(assumed monomers; **ink-jet** printer head
with good abrasion resistance and **ink** repelling)

RN 848229-99-2 HCPLUS

CN INDEX NAME NOT YET ASSIGNED

CM 1

CRN 847200-62-8
CMF (C₂ H₆ O Si)_n C₁₀ H₂₄ O₃ Si₂
CCI PMS

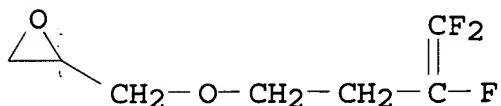


CM 2

CRN 848229-98-1
 CMF (C7 H9 F3 O2 . C6 F10 O)x
 CCI PMS

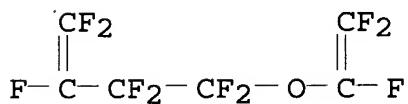
CM 3

CRN 674308-49-7
 CMF C7 H9 F3 O2



CM 4

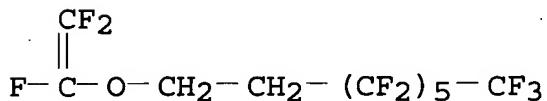
CRN 69818-05-9
 CMF C6 F10 O



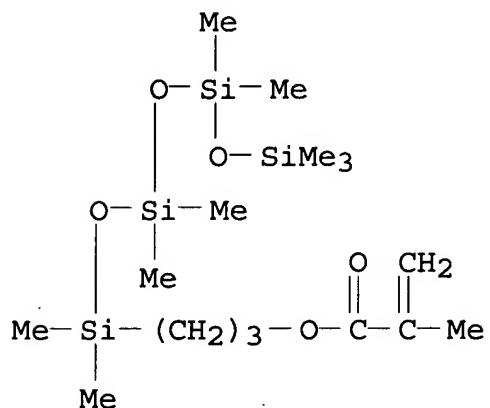
RN 848366-82-5 HCPLUS
 CN 2-Propenoic acid, 2-methyl-, 3-(nonamethyltetrasiloxanyl)propyl ester, polymer with 1,1,2,3,3,4,4,4-octafluoro-1-butene, oxiranylmethyl 2-methyl-2-propenoate and 1,1,1,2,2,3,3,4,4,5,5,6,6-tridecafluoro-8-[(trifluoroethenyl)oxy]octane, graft (9CI) (CA INDEX NAME)

CM 1

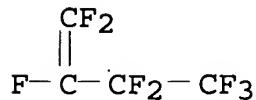
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 CMF C10 H4 F16 O



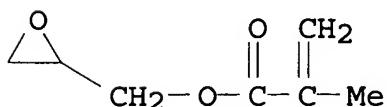
CM 2

CRN 77865-90-8
CMF C16 H38 O5 Si4

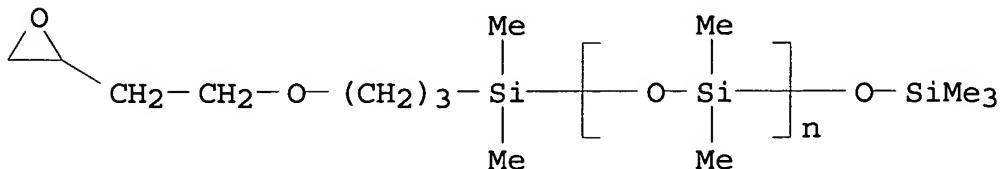
CM 3

CRN 357-26-6
CMF C4 F8

CM 4

CRN 106-91-2
CMF C7 H10 O3IT 847200-61-7DP, reaction products with graft fluoropolymer
(ink-jet printer head with good abrasion)

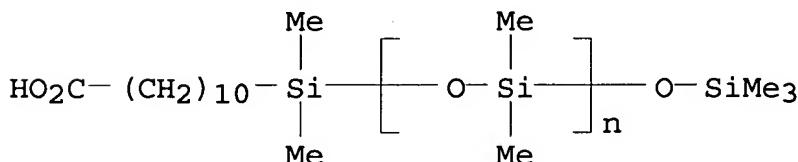
resistance and **ink** repelling)
 RN 847200-61-7 HCPLUS
 CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(2-oxiranyloxy)propyl]silyl]- ω -[(trimethylsilyl)oxy] - (9CI)
 (CA INDEX NAME)



IT 658079-18-6P
 (repellent liner; **ink-jet** printer head with
 good abrasion resistance and **ink** repelling)
 RN 658079-18-6 HCPLUS
 CN Oxirane, [[(2,3,3-trifluoro-2-propenyl)oxy]methyl] -, polymer with
 1,1,2,3,3,4,4,4-octafluoro-1-butene, ester α -[(10-
 carboxydecyl)dimethylsilyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], graft (9CI) (CA INDEX NAME)

CM 1

CRN 188921-66-6
 CMF (C₂ H₆ O Si)_n C₁₆ H₃₆ O₃ Si₂
 CCI PMS



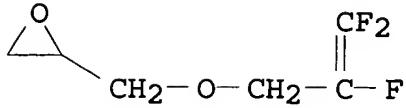
CM 2

CRN 658079-17-5
 CMF (C₆ H₇ F₃ O₂ . C₄ F₈)_x
 CCI PMS

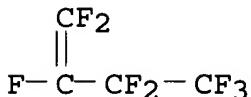
CM 3

CRN 658074-78-3

CMF C6 H7 F3 O2



CM 4

CRN 357-26-6
CMF C4 F8

IC ICM B41J002-015
 NCL 347045000
 CC 74-6 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38, 42
 ST fluoropolymer siloxane block copolymer **ink** repelling
 head printer; jet printer head **ink** repelling coating
 IT Polysiloxanes, preparation
 (fluorine-containing, graft block; **ink-jet**
 printer head with good abrasion resistance and **ink**
 repelling)
 IT **Ink-jet** printers
 (**ink-jet** printer head with good abrasion
 resistance and **ink** repelling)
 IT Coating materials
 (linings; **ink-jet** printer head with good
 abrasion resistance and **ink** repelling)
 IT Fluoropolymers, preparation
 (polysiloxane-, graft block; **ink-jet**
 printer head with good abrasion resistance and **ink**
 repelling)
 IT 848229-93-6DP, reaction products with glycidyl-containing
 polysiloxanes 848229-97-0DP, trimethylsilyl ether
 848229-99-2DP, trimethylsilyl ether 848230-00-2DP,
 trimethylsilyl ether 848230-13-7P 848230-15-9P 848230-16-0P
 848230-18-2P 848230-19-3P 848366-81-4P 848366-82-5P
 (assumed monomers; **ink-jet** printer head

with good abrasion resistance and **ink** repelling)

IT 29570-58-9DP, Dipentaerythritol hexaacrylate, crosslinked products

with block graft fluoropolymer-polysiloxanes 60506-81-2DP, Dipentaerythritol pentaacrylate, crosslinked products with block graft fluoropolymer-polysiloxanes 848366-83-6P

(**ink-jet** printer head with good abrasion resistance and **ink** repelling)

IT 106-91-2DP, Glycidyl methacrylate, reaction products with carboxyphenylmethyl-terminated fluoropolymer, graft copolymer with

functional siloxane 868-77-9DP, 2-Hydroxyethyl methacrylate, graft copolymer with fluoro macromer and functional siloxane 30674-80-7DP, 2-(Methacryloyloxy)ethyl isocyanate, reaction products with carboxy-terminated fluoropolymer, block graft copolymer with functional siloxanes 111481-56-2DP, graft copolymer with fluoropolymer and methacrylate ester 667457-02-5DP, carboxy-terminated, reaction products with 2-(methacryloyloxy)ethyl isocyanate, graft copolymer with functional siloxanes 667457-04-7DP, carboxyphenylmethyl-terminated, reaction products with glycidyl methacrylate, graft copolymer with functional siloxane and methacrylate

847200-61-7DP, reaction products with graft fluoropolymer

848229-95-8DP, graft copolymers with block fluoropolymers

848230-04-6DP, graft copolymer with fluoro macromer and functional siloxane 848230-08-0DP, graft copolymer with fluoro macromer and

functional siloxane

and methacrylate ester

(**ink-jet** printer head with good abrasion resistance and **ink** repelling)

IT 658079-18-6P

(repellent liner; **ink-jet** printer head with good abrasion resistance and **ink** repelling)

L37 ANSWER 2 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2005:238651 HCAPLUS

DOCUMENT NUMBER: 142:325972

TITLE: Thermal donor for high-speed printing

INVENTOR(S): Foster, David G.; Gray, Maurice L.; Kung, Teh-Ming; York, William M.; Pope, Brian T.

PATENT ASSIGNEE(S): Eastman Kodak Company, USA

SOURCE: U.S. Pat. Appl. Publ., 11 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	
DATE				
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US 2005059550	A1	20050317	US 2003-667065	
2003				
0917	WO 2005032839	A1	20050414	WO 2004-US28455
2004				
0901	W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			

PRIORITY APPLN. INFO.: US 2003-667065 A

2003

0917

AB A dye-donor element including a dye-donor layer is described, wherein the dye-donor element includes a stick preventative agent (e.g., polysiloxane). The dye-donor element is capable of printing an image on a receiver element at a line speed of 2 ms/line or less while maintaining a print d. of at least two, and a print to fail value of at least four. A print assembly including the dye-donor element and a receiver element is also described, as well as a method of printing using the dye-donor element.

IC ICM B41M005-38

NCL 503227000

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT **Polysiloxanes**, uses
(3-aminopropyl Me, di-Me, release agent; GP 4, GP 6; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(Dow Corning 18, release agent; Dow Corning 11, GP 5, GP 70S, GP 7200, GP 71S; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(Me stearyl, release agent; PS 130; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(amino, GP-RA 156, release agent; GP 4E, GP 50A, GP-RA 157; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(aminoalkyl, release agent; GP 7100; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethers with **polyethylene-polypropylene glycol** mono-Me ether, release agent; Silwet L 7001; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated propoxylated, release agent; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated, release agent; DBE 224; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polyoxyalkylenes**, uses
(di-Me, Me hydrogen **polysiloxane** -, release agent; Dow 190; release agents for use in thermal donor for high-speed printing with reduced sticking complication)

IT **Polysiloxanes**, uses
(di-Me, Me hydrogen, **polyoxyalkylene-**, release agent; Dow 190; release agents for use in thermal donor for high-speed printing with

reduced sticking complication)

IT **Polysiloxanes**, uses
(di-Me, Me trifluoropropyl,
hydroxy-terminated, release agent, PS 187; release agents for
use in thermal donor for high-speed printing with reduced
sticking complication)

IT **Polysiloxanes**, uses
(epoxy, release agent; GP 32, GP 502; release agents for use
in
thermal donor for high-speed printing with reduced sticking
complication)

IT **Polysiloxanes**, uses
(fluorine-containing, release agents; release agents for use
in
thermal donor for high-speed printing with reduced sticking
complication)

IT **Polysiloxanes**, uses
(polyester-, release agent; Byk 371; release agents for use in
thermal donor for high-speed printing with reduced sticking
complication)

IT **Polyesters**, uses
(**polysiloxane**-, release agent; Byk 371; release
agents for use in thermal donor for high-speed printing with
reduced sticking complication)

IT **Epoxy resins**, uses
(**polysiloxane**-, release agent; GP 32, GP 502; release
agents for use in thermal donor for high-speed printing with
reduced sticking complication)

IT **Fluoropolymers**, uses
(**polysiloxane**-, release agents; release agents for
use in thermal donor for high-speed printing with reduced
sticking complication)

IT 156395-52-7, **Dimethylsilanediol**-methyl-3,3,3-
trifluoropropylsilanediol copolymer
(assumed monomers; release agent; PS 187; release agents for
use in thermal donor for high-speed printing with reduced
sticking complication)

IT 9002-88-4, Vybar 103 31900-57-9D, **Dimethylsilanediol**
polymer, aminopropyldimethylsilyl-terminated 97917-34-5, PS 513
158421-85-3, GP 501 159791-74-9, GP-134 195889-49-7, S 379N
219997-22-5, Dow Corning 57 568593-97-5, Zonyl FSG
848044-83-7, Dow Corning 163 848045-64-7, Zonyl 9233B
(release agent; release agents for use in thermal donor for
high-speed printing with reduced sticking complication)

DOCUMENT NUMBER: 142:123246
 TITLE: Holographic **recording** material, its
 manufacture, and **recording** method
 INVENTOR(S): Sasa, Nobumasa
 PATENT ASSIGNEE(S): Konica Minolta Medical & Graphic, Inc., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 24 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	-----	-----	-----
-----	JP 2005010187	A2	20050113	JP 2003-170646

2003

0616

PRIORITY APPLN. INFO.: JP 2003-170646

2003

0616

OTHER SOURCE(S): MARPAT 142:123246

AB The material contains (A) photo-image forming composition containing a

cationic polymerizable compound and S-containing photo-acid generator

and (B) an inorg. or organic matrix precursor. The material is manufactured by mixing A and B, coating the mixture on a support, and

curing the matrix-forming compds. The material is imagewise irradiated with actinic ray for holog. image formation. The material shows high sensitivity, dimensional stability, and high refractivity contrast.

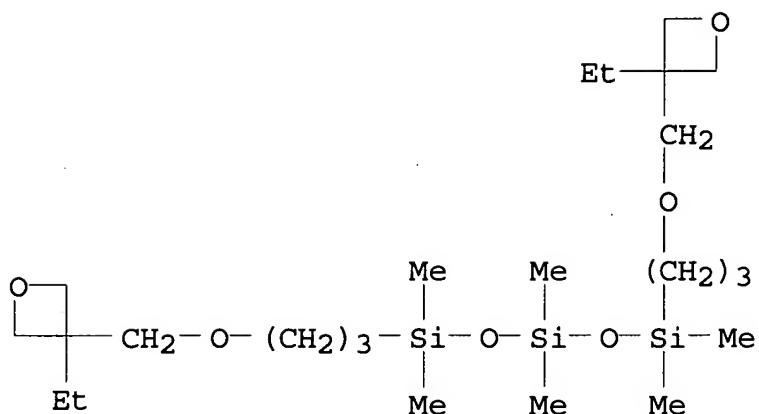
IT 820232-92-6P

(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

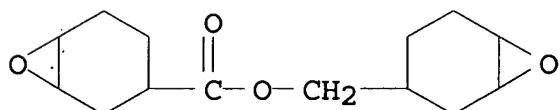
RN 820232-92-6 HCPLUS

CN 7-Oxabicyclo[4.1.0]heptane-3-carboxylic acid, 7-oxabicyclo[4.1.0]hept-3-ylmethyl ester, polymer with 1,5-bis[3-[(3-ethyl-3-oxetanyl)methoxy]propyl]-1,1,3,3,5,5-hexamethyltrisiloxane (9CI) (CA INDEX NAME)

CM 1

CRN 144993-30-6
CMF C24 H52 O6 Si3

CM 2

CRN 2386-87-0
CMF C14 H20 O4

IC ICM G03H001-02
ICS G03F007-004; G03F007-032

CC 74-8 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

ST holog **recording** material matrix precursor; cationic polymerizable compn sulfur photoacid generator

IT Polysiloxanes, uses
(Me Ph; holog. **recording** material comprising cationic polymerizable image forming composition and matrix precursor)

IT Polyoxyalkylenes, preparation
(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT Holographic **recording** materials

(holog. **recording** material comprising cationic polymerizable image forming composition and matrix precursor)

IT Polyurethanes, preparation
(polyoxyalkylene-, matrix; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 5551-72-4, NAI 101 823819-47-2, PI 105
(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 29616-43-1P, Celloxide 3000 120309-91-3P 820232-90-4P
820232-92-6P 820232-93-7P
(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 9005-12-3, Poly[oxy(methylphenylsilylene)] 31230-04-3,
Poly(Methylphenylsiloxane)
(holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 25322-69-4DP, Polypropylene glycol, copolymers with diisocyanate-terminated polypropylene glycol 25322-69-4DP,
Polypropylene glycol, diisocyanate-terminated, copolymers with polypropylene glycol
(matrix; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 104558-95-4, CyraCure UVI 6990 205944-57-6, SP 152
(photoacid generator; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

IT 820232-94-8
(sensitizer; holog. **recording** material comprising cationic polymerizable composition and matrix precursor)

L37 ANSWER 4 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2005:9264 HCAPLUS
 DOCUMENT NUMBER: 142:103198
 TITLE: Inkjet **recording** materials
 containing siloxane copolymer surfactants
 INVENTOR(S): Chen, Tienteh
 PATENT ASSIGNEE(S): Hewlett-Packard Development Company, L.P.,
 USA
 SOURCE: Eur. Pat. Appl., 11 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			

EP 1493591

A2 20050105

EP 2004-1605

2004

0126

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,
MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ,
EE, HU, SK

my Case US 2005003112 A1 20050106 US 2003-613497

2003

0702

JP 2005022415 A2 20050127 JP 2004-196255

2004

0702

PRIORITY APPLN. INFO.: US 2003-613497 A

2003

0702

AB A print medium having improved image quality and permanence. The print medium comprises a coated paper base and an ink-receiving layer. The ink-receiving layer comprises a nonionic siloxane copolymer surfactant. A method of forming the print medium is also disclosed. In addition, a method of printing an image having

improved image quality and permanence is disclosed.

IC ICM B41M005-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST ink jet recording material siloxane copolymer surfactant

IT Alcohols, uses

(C11-15-secondary, ethoxylated; ink jet recording materials containing siloxane copolymer surfactants)

IT Polyethers, uses

(di-Me siloxane-; ink jet recording materials containing siloxane copolymer surfactants)

IT Polysiloxanes, uses

(di-Me, 3-hydroxypropyl Me, ethers with polyethylene glycol mono-Me ether; ink jet recording

materials containing **siloxane** copolymer surfactants)

IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethers with
polyethylene-polypropylene glycol
mono-Me ether; ink jet **recording** materials containing
siloxane copolymer surfactants)

IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated
propoxylated; ink jet **recording** materials containing
siloxane copolymer surfactants)

IT **Polyoxyalkylenes**, uses
(di-Me, Me hydrogen **polysiloxane**
-; ink jet **recording** materials containing
siloxane copolymer surfactants)

IT **Polysiloxanes**, uses
(di-Me, Me hydrogen,
polyoxyalkylene-; ink jet **recording** materials
containing **siloxane** copolymer surfactants)

IT **Polysiloxanes**, uses
(di-Me, hydroxy-terminated, ethoxylated
propoxylated; ink jet **recording** materials containing
siloxane copolymer surfactants)

IT **Polysiloxanes**, uses
(di-Me, polyether-; ink jet
recording materials containing **siloxane** copolymer
surfactants)

IT Ink-jet printing
Surfactants
(ink jet **recording** materials containing **siloxane**
copolymer surfactants)

IT 9002-93-1, Triton X-405 9005-64-5, Tween 20 9005-66-7, Tween
40 9014-85-1, Surfynol 420 51569-39-2, Olin 10G
107397-59-1,
Tetronic 90R4 110617-70-4, Tetronic 704 441052-10-4, Silwet L
7220 587848-36-0, Silwet L 7650 691397-13-4, Pluronic L44
(ink jet **recording** materials containing **siloxane**
copolymer surfactants)

L37 ANSWER 5 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2004:878586 HCAPLUS
 DOCUMENT NUMBER: 141:372733
 TITLE: Method for use of polymer coated paper or
board as reusable printing substrate and
printed product
 INVENTOR(S): Haakana, Sami Pekka Juhani; Vesanto, Risto
 PATENT ASSIGNEE(S): Finnish Chemicals Oy, Finland; Stora Enso Oyj
 SOURCE: PCT Int. Appl., 16 pp.

DOCUMENT TYPE: CODEN: PIXXD2
 LANGUAGE: Patent
 FAMILY ACC. NUM. COUNT: English
 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	-----	-----	-----	-----
	-----	-----	-----	-----
	WO 2004090642	A1	20041021	WO 2004-FI212

2004

0407

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ,
 CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG,
 ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP,
 KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD,
 MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL,
 PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR,
 TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
 RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW,
 AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY,
 CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC,
 NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM,
 GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

FI 2003000541	A	20041011	FI 2003-541
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2003

0410

PRIORITY APPLN. INFO.:

FI 2003-541

A

2003

0410

AB The invention relates to a method for using a polymer-coated paper

or board as a printing substrate, to the printed product thus obtained and to the use of the coating. The invention relates to repeated use of the printing substrate, so that the printing ink is removed with a solvent from the surface that has been printed once, and the printing substrate thus cleaned is used for reprint. In accordance with the invention, the printing

surface is formed of polysiloxane, to which polyester or styrene acrylate-based toners attach so as to be irremovable by mech. means, yet removable by washing with a suitable solvent, such as acetone, for instance. A polysiloxane-coated paper or board is suitable especially for electro-photog. print with a dry toner, which

can be fixed to the printing surface by fusion.

IT 778624-42-3P

(use of polymer coated paper or board as reusable printing substrate)

RN 778624-42-3 HCPLUS

CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with diethoxymethyl[3-(oxiranylmethoxy)propyl]silane and silica (9CI) (CA INDEX NAME)

CM 1

CRN 7631-86-9

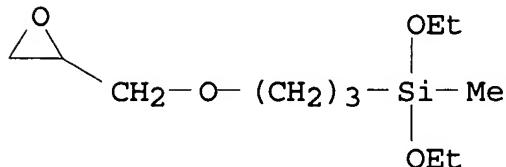
CMF O2 Si

O=Si=O

CM 2

CRN 2897-60-1

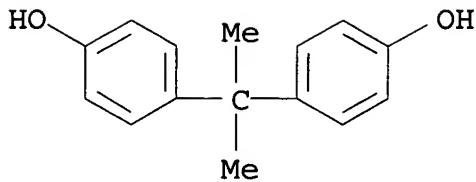
CMF C11 H24 O4 Si



CM 3

CRN 80-05-7

CMF C15 H16 O2



IC ICM G03G005-00

ICS G03G007-00; B41M005-00; B41M007-00; D21H019-32

CC 74-3 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)

Section cross-reference(s): 38

IT 778624-40-1P 778624-41-2P 778624-42-3P

(use of polymer coated paper or board as reusable printing
substrate)REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS

AVAILABLE

IN THE RE FORMAT

L37 ANSWER 6 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:857021 HCAPLUS

DOCUMENT NUMBER: 141:358156

TITLE: Holographic **recording** medium and
recording method

INVENTOR(S): Takeyama, Toshihisa

PATENT ASSIGNEE(S): Japan

SOURCE: U.S. Pat. Appl. Publ., 23 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----
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US 2004202942	A1	20041014	US 2004-815490

2004

0331

PRIORITY APPLN. INFO.: JP 2003-105006

A

2003

0409

JP 2003-194816

A

2003

0710

OTHER SOURCE(S) : MARPAT 141:358156

AB A holog. **recording** contains a first substrate and a second substrate having a holog. **recording** layer between the first substrate and the second substrate, the holog. **recording** layer containing: (A) a binder compound having a reactive group capable of cationic polymerization; (B) a polymerizable compound having an ethylenic double bound in the mol.; (C) a photoinitiator; and (D) a crosslinking agent which reacts with the reactive group in the binder compound, the crosslinking agent being a thermal cationic polymerization initiator. The feature of the present invention is to provide holog. **recording** media having a high sensitivity and a low volume decreasing property, and a holog. **recording** method employing the media.

IT 774592-40-4P (holog. **recording** medium and **recording** method)

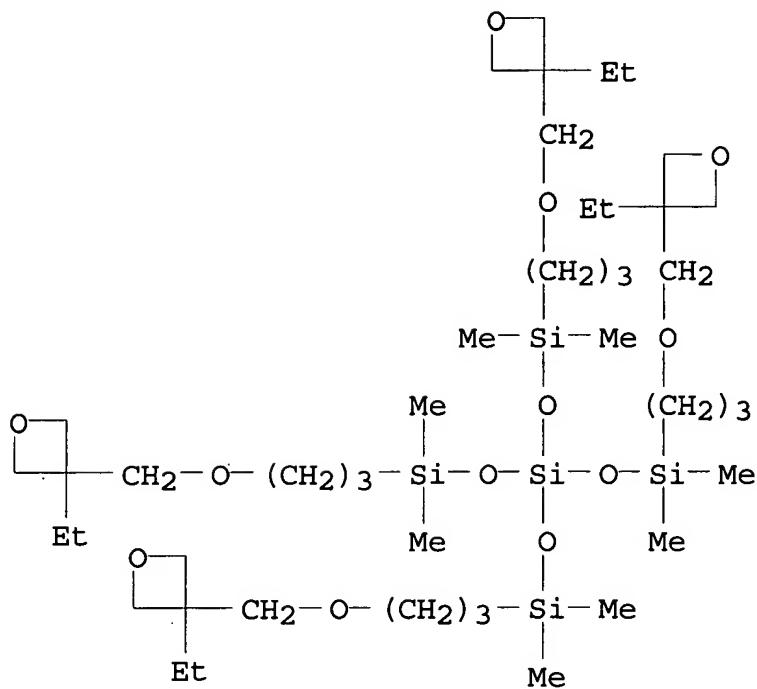
RN 774592-40-4 HCPLUS

CN Trisiloxane, 1,5-bis[3-[(3-ethyl-3-oxetanyl)methoxy]propyl]-3,3-bis[[[3-[(3-ethyl-3-oxetanyl)methoxy]propyl]dimethylsilyl]oxy]-1,1,5,5-tetramethyl-, polymer with 2,2'-[2-ethyl-2-[(oxiranylmethoxy)methyl]-1,3-propanediyl]bis(oxymethylene)]bis[oxirane] and 2,2'-(1-methylethylidene)bis(4,1-phenyleneoxymethylene)]bis[oxirane] (9CI) (CA INDEX NAME)

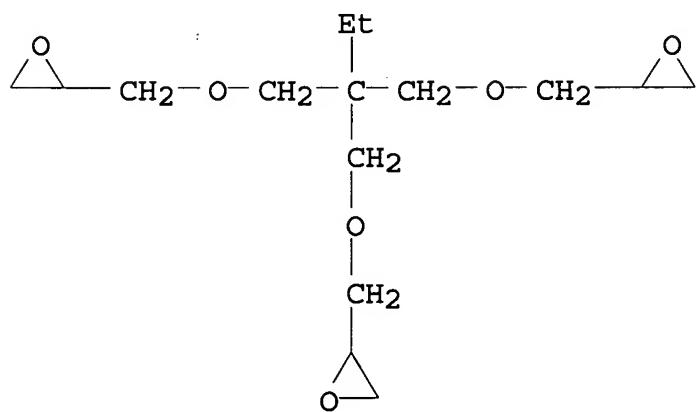
CM 1

CRN 144993-31-7

CMF C44 H92 O12 Si5

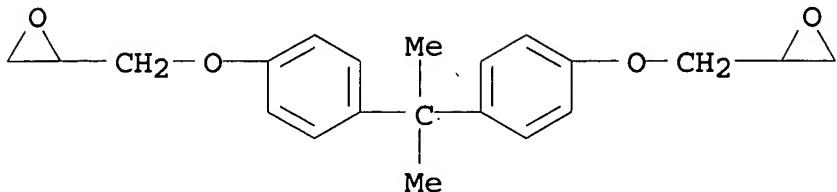


CM 2

CRN 3454-29-3
CMF C15 H26 O6

CM 3

CRN 1675-54-3
 CMF C21 H24 O4



IC ICM G03H001-00
 NCL 430001000
 CC 74-8 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38
 ST holog recording medium card
 IT Holographic recording materials
 (holog. recording medium and recording method)
 IT Polyethers, preparation
 (holog. recording medium and recording method)
 IT 26142-30-3, Polypropylene glycol diglycidyl ether
 (Epolight 200P; holog. recording medium and recording method)
 IT 774592-43-7, NK Ester A-CMP 1E
 (NK Ester A-CMP 1E; holog. recording medium and recording method)
 IT 64022-15-7, NK Ester A-NP 1E
 (NK Ester A-NP 1E; holog. recording medium and recording method)
 IT 7347-19-5, New Frontier BR-31
 (New Frontier BR-31; holog. recording medium and recording method)
 IT 67006-39-7, New Frontier BR-42M
 (New Frontier BR-42M; holog. recording medium and recording method)
 IT 774592-34-6P 774592-35-7P 774592-36-8P 774592-37-9P
 774592-38-0P 774592-39-1P 774592-40-4P 774592-41-5P,
 4-Bromostyrene-4-chlorophenyl acrylate copolymer 774592-42-6P,
 4-Bromostyrene-New Frontier BR-31 copolymer 774592-44-8P
 774592-45-9P 774592-46-0P 774592-47-1P 774592-48-2P
 (holog. recording medium and recording method)
 IT 2039-82-9, 4-Bromostyrene 3047-32-3, 3-Ethyl-3-

hydroxymethyloxetane 3454-29-3, Trimethylolpropane triglycidyl ether 3897-65-2, 3-Ethyl-3-(phenoxyethyl)oxetane 13633-87-9, 4-Chlorophenyl acrylate 24293-30-9 25085-99-8, Epo Toho YD 127 32760-80-8 51156-89-9, Tribromophenyl methacrylate 52794-68-0, Tribromophenyl acrylate 125051-32-3 125662-54-6 133152-67-7 134507-97-4 134508-03-5 134508-05-7 135842-78-3 144993-31-7 180423-87-4 186419-14-7 220666-63-7 300822-65-5 331623-03-1 773058-26-7 773058-27-8 774592-32-4 774592-33-5 774594-70-6
(holog. recording medium and recording method)

L37 ANSWER 7 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2004:824978 HCAPLUS
 DOCUMENT NUMBER: 141:340478
 TITLE: Holographic recording medium and recording method
 INVENTOR(S): Takeyama, Toshihisa
 PATENT ASSIGNEE(S): Konica Minolta Holdings, Inc., Japan
 SOURCE: U.S. Pat. Appl. Publ., 21 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	US 2004197670	A1	20041007	US 2004-802143 <i>Filed 03/16/2004</i>
2004				
0316	JP 2004287138	A2	20041014	JP 2003-79523
2003				
0324	WO 2004086151	A1	20041007	WO 2004-JP3684
2004				
0318	W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG,			

ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE,
 KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG,
 MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT,
 RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT,
 TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW
 RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW,
 AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY,
 CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC,
 NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM,
 GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRIORITY APPLN. INFO.:

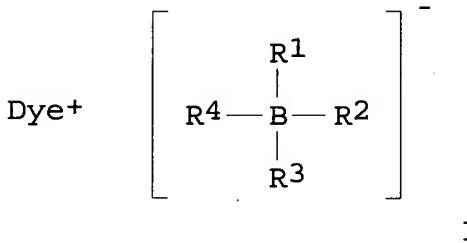
JP 2003-79523

A

2003

0324

OTHER SOURCE(S) : MARPAT 141:340478
 GI



AB A holog. recording medium having high sensitivity comprises a first substrate and a second substrate having a holog.

recording layer between the first substrate and the second substrate, the holog. recording layer containing: (A) a binder compound having a reactive group; (B) a polymerizable compound

having an ethylenic double bond; (C) a photoinitiator; and (D) a crosslinking agent which reacts with the reactive group in the binder compound, wherein the photoinitiator contains a compound represented by formula I (Dye⁺ = cationic dye; R₁-R₄ = alkyl, aryl, aralkyl, alkenyl, alkynyl, heterocyclic, cyano; provided that two or more of R₁-R₄ can form a ring).

IT 771534-35-1P 773091-90-0P 773091-91-1P
 773091-92-2P 773091-93-3P 773091-94-4P
 773091-95-5P 773091-96-6P 773091-97-7P

773091-98-8P 773092-00-5P 773092-01-6P

773092-02-7P 773092-03-8P

(holog. recording medium and recording
method)

RN 771534-35-1 HCAPLUS

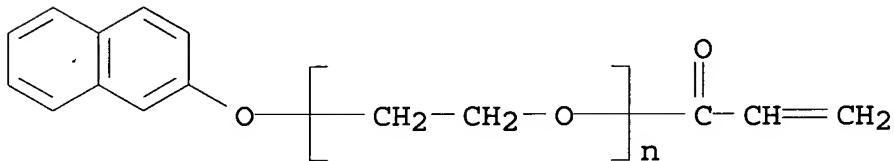
CN Poly[oxy(dimethylsilylene)], α -[[3-(2-hydroxyethoxy)propyl]dimethylsilyl]- ω -[[[3-(2-hydroxyethoxy)propyl]dimethylsilyl]oxy]-, polymer with α,α' -[(1-methylethylidene)di-4,1-phenylene]bis[ω -(oxiranylmethoxy)poly[oxy(methyl-1,2-ethanediyl)]] and α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7

CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂

CCI PMS



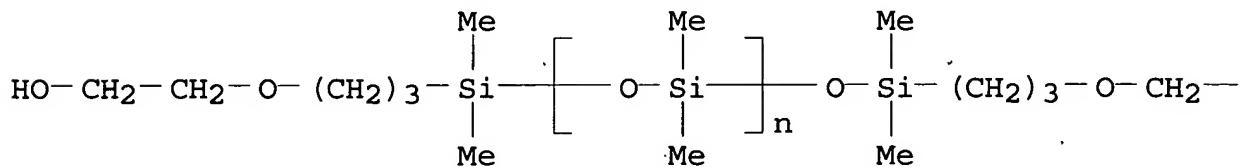
CM 2

CRN 156327-07-0

CMF (C₂ H₆ O Si)_n C₁₄ H₃₄ O₅ Si₂

CCI PMS

PAGE 1-A



PAGE 1-B

— CH₂— OH

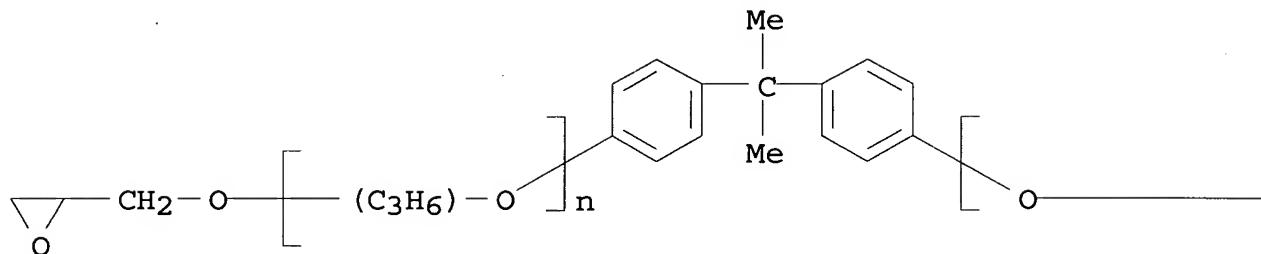
CM 3

CRN 55236-42-5

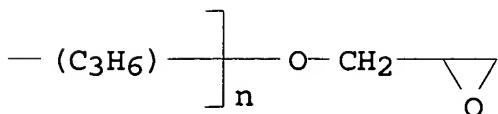
CMF (C₃ H₆ O)_n (C₃ H₆ O)_n C₂₁ H₂₄ O₄

CCI IDS, PMS

PAGE 1-A



PAGE 1-B

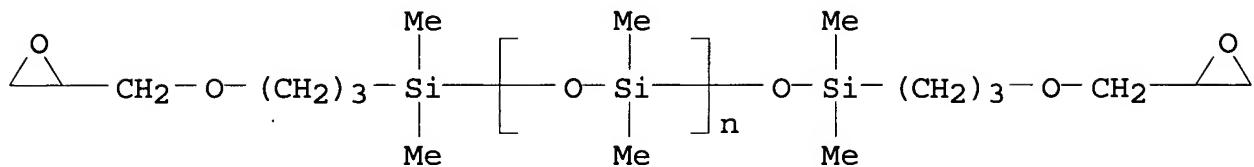


RN 773091-90-0 HCPLUS

CN 2-Propenoic acid, 4-chlorophenyl ester, polymer with 2,2-bis[(3-mercaptopropanoate)methyl]-1,3-propanediyl bis(3-mercaptopropanoate) and α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] (9CI) (CA INDEX NAME)

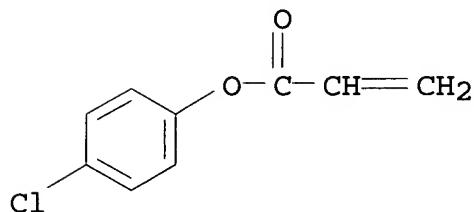
CM 1

CRN 130167-23-6
 CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂
 CCI PMS



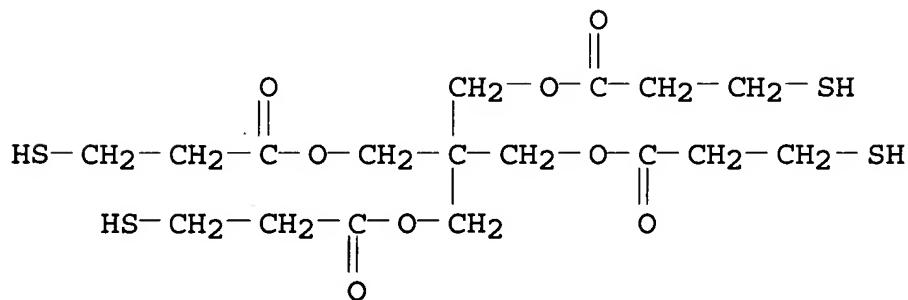
CM 2

CRN 13633-87-9
 CMF C₉ H₇ Cl O₂



CM 3

CRN 7575-23-7
 CMF C₁₇ H₂₈ O₈ S₄



RN 773091-91-1 HCAPLUS

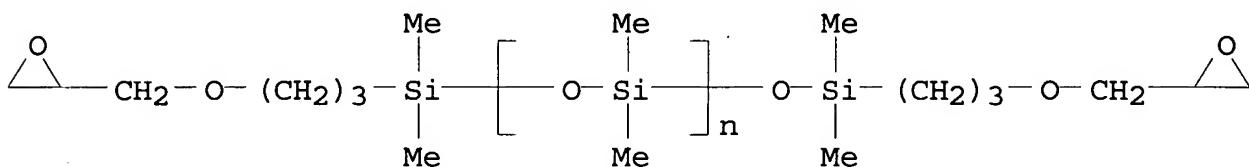
CN 2-Propenoic acid, 4-chlorophenyl ester, polymer with
 2,2-bis[(3-mercaptopropanoate)methyl]-1,3-propanediyl
 bis(3-mercaptopropanoate), α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and
 α,α' -[(1-methylethylidene)di-4,1-phenylene]bis[ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

CM 1

CRN 130167-23-6

CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

CCI PMS



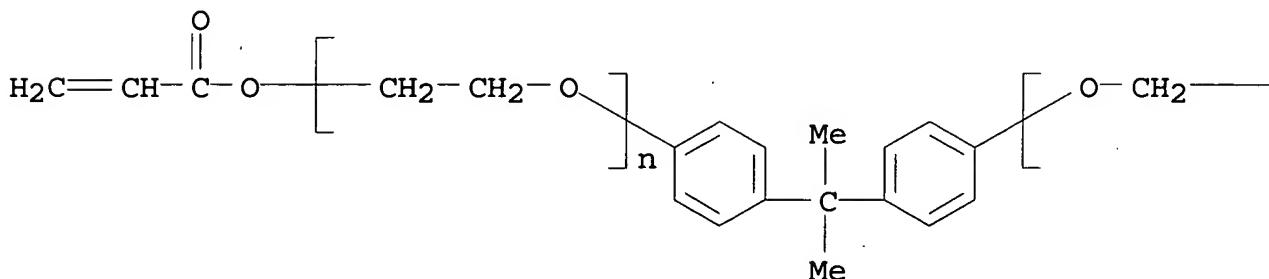
CM 2

CRN 64401-02-1

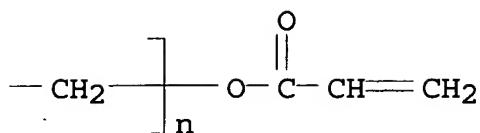
CMF (C₂ H₄ O)_n (C₂ H₄ O)_n C₂₁ H₂₀ O₄

CCI PMS

PAGE 1-A

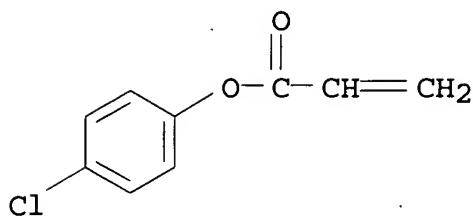


PAGE 1-B



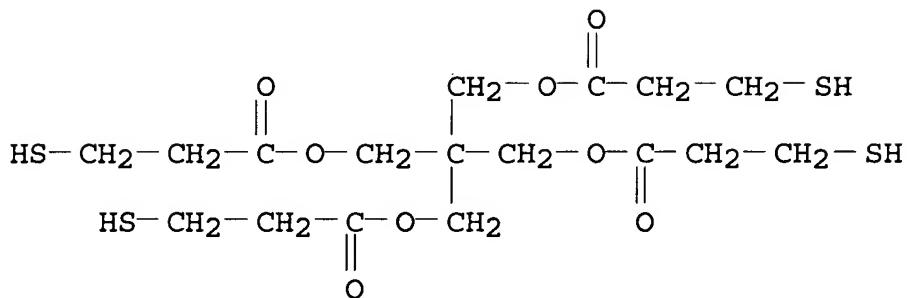
CM 3

CRN 13633-87-9
 CMF C9 H7 Cl O2



CM 4

CRN 7575-23-7
 CMF C17 H28 O8 S4



RN 773091-92-2 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2-[4-(1-methyl-1-phenylethyl)phenoxy]ethyl ester, polymer with 2,2-bis[(3-mercaptopropanoyl)-1,3-propanediyl] bis(3-mercaptopropanoate) and

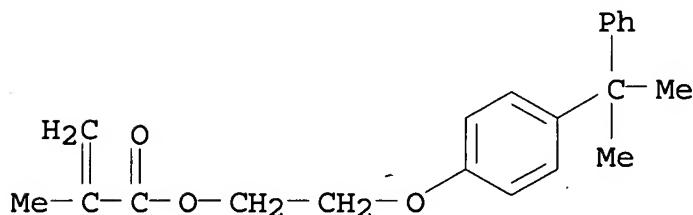
α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -

[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] (9CI) (CA INDEX NAME)

CM 1

CRN 191853-23-3

CMF C21 H24 O3

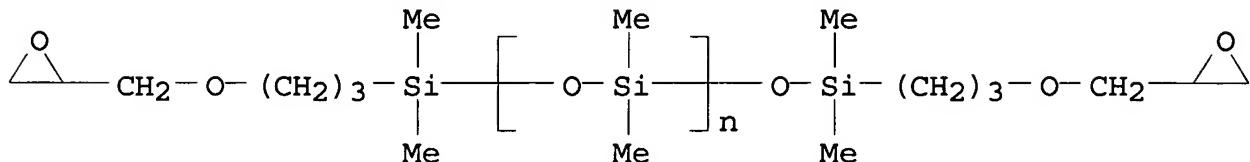


CM 2

CRN 130167-23-6

CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

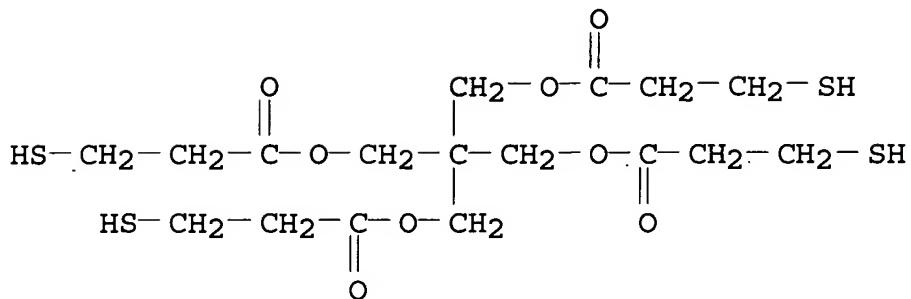
CCI PMS



CM 3

CRN 7575-23-7

CMF C₁₇ H₂₈ O₈ S₄



RN 773091-93-3 HCAPLUS

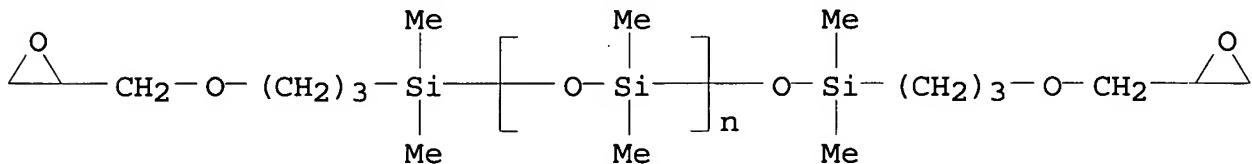
CN 2-Propenoic acid, 2-[4-(1-methyl-1-phenylethyl)phenoxy]ethyl ester, polymer with 2,2-bis[(3-mercaptopropanoate)methyl]-1,3-propanediyl bis(3-mercaptopropanoate) and α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] (9CI) (CA INDEX NAME)

CM 1

CRN 130167-23-6

CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

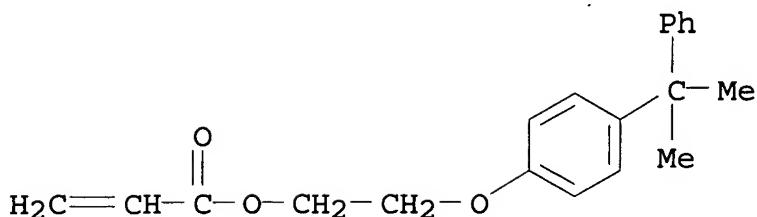
CCI PMS



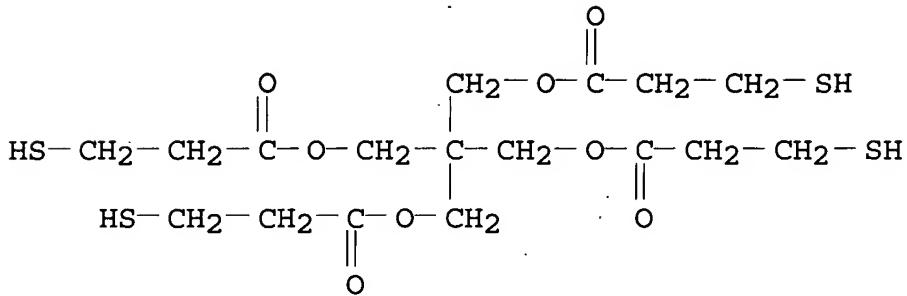
CM 2

CRN 86148-08-5

CMF C20 H22 O3



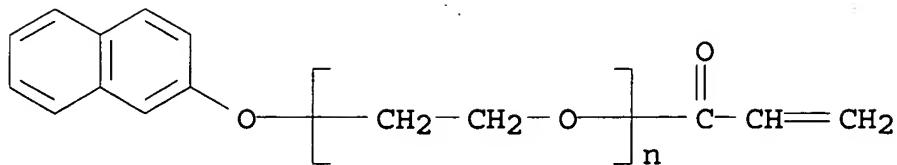
CM 3

CRN 7575-23-7
CMF C17 H28 O8 S4

RN 773091-94-4 HCPLUS.
 CN 2-Propenoic acid, 2-[4-(1-methyl-1-phenylethyl)phenoxy]ethyl ester, polymer with 2,2-bis[(3-mercaptopropanoate)methyl]-1,3-propanediyl bis(3-mercaptopropanoate), α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and α -(1-oxo-2-propenyl)- ω -(2-naphthalenyl)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7
CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂
CCI PMS

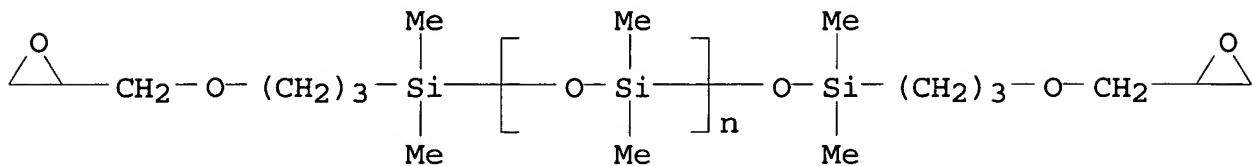


CM 2

CRN 130167-23-6

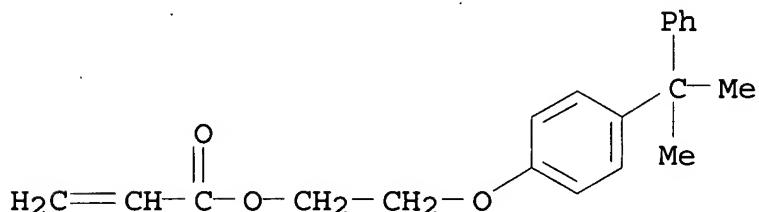
CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

CCI PMS



CM 3

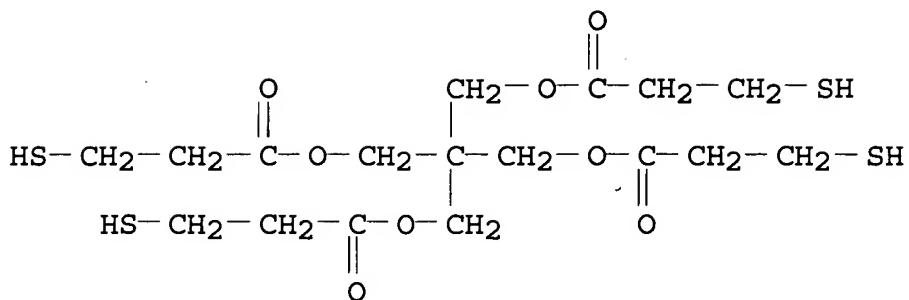
CRN 86148-08-5

CMF C₂₀ H₂₂ O₃

CM 4

CRN 7575-23-7

CMF C₁₇ H₂₈ O₈ S₄



RN 773091-95-5 HCAPLUS

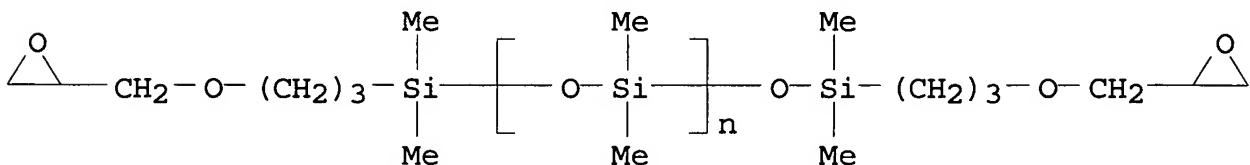
CN Propanoic acid, 3-mercaptop-, 2,2-bis[(3-mercaptop-1-oxopropoxy)methyl]-1,3-propanediyl ester, polymer with α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and α -(1-oxo-2-propenyl)- ω -([1,1'-biphenyl]-2-yloxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 130167-23-6

CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

CCI PMS

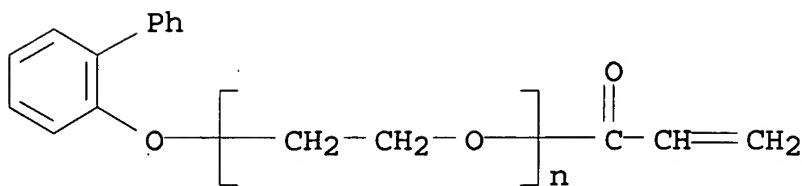


CM 2

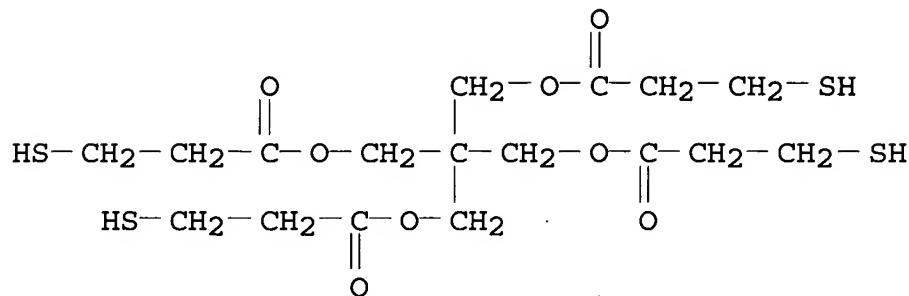
CRN 72009-86-0

CMF (C₂ H₄ O)_n C₁₅ H₁₂ O₂

CCI PMS



CM 3

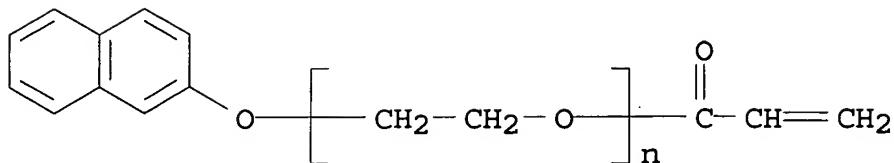
CRN 7575-23-7
CMF C17 H28 O8 S4

RN 773091-96-6 HCPLUS
 CN Propanoic acid, 3-mercaptop-, 2,2-bis[(3-mercaptop-1-oxoproxy)methyl]-1,3-propanediyl ester, polymer with α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -

[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7
CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂
CCI PMS

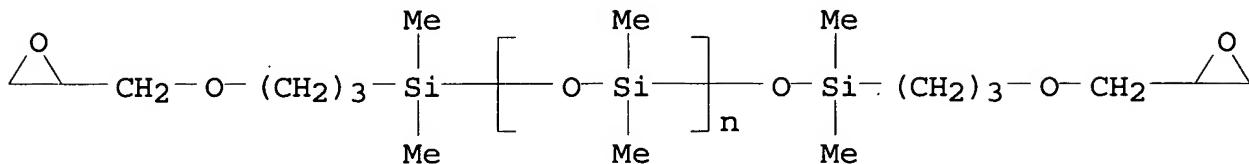


CM 2

CRN 130167-23-6

CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

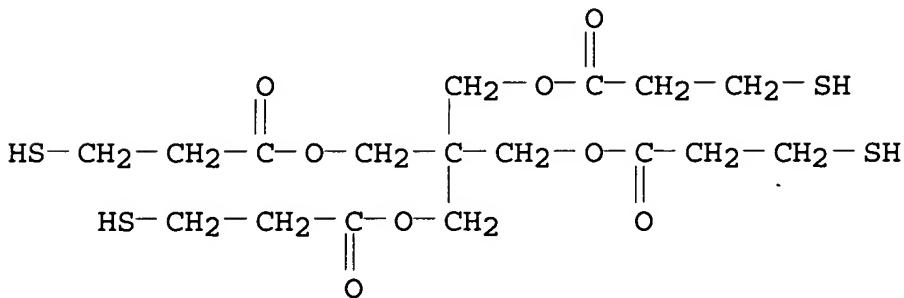
CCI PMS



CM 3

CRN 7575-23-7

CMF C17 H28 O8 S4



RN 773091-97-7 HCAPLUS

CN 2-Propenoic acid, 4-chlorophenyl ester, polymer with 2,2-bis[(3-mercaptopropanoate)methyl]-1,3-propanediyl bis(3-mercaptopropanoate), α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]poly[oxy(dimethylsilylene)] and

α, α' -[9H-fluoren-9-ylidenebis([1,1'-biphenyl]-5,2-diyl)]bis[ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

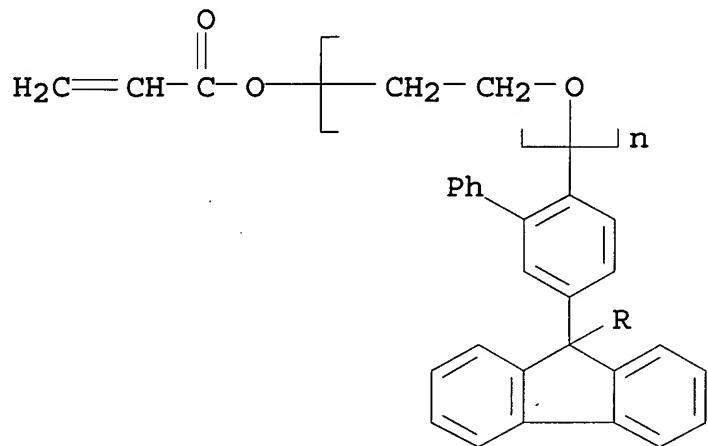
CM 1

CRN 337966-87-7

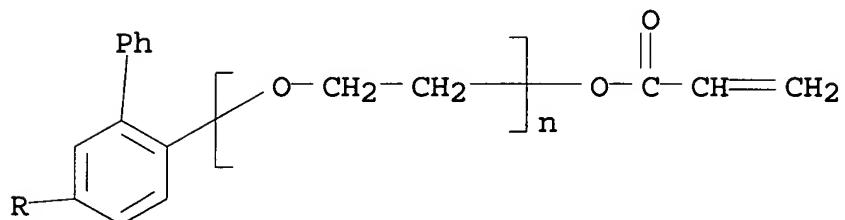
CMF (C₂ H₄ O)_n (C₂ H₄ O)_n C₄₃ H₃₀ O₄

CCI PMS

PAGE 1-A



PAGE 2-A

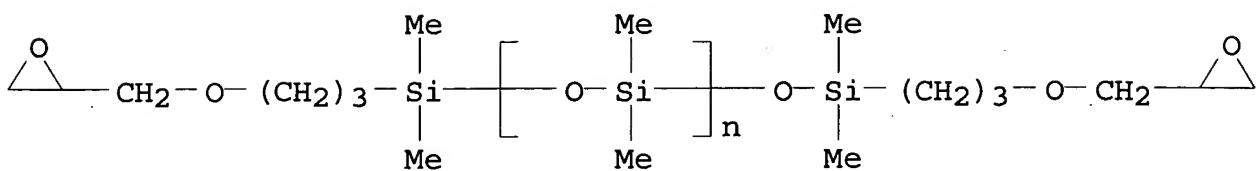


CM 2

CRN 130167-23-6

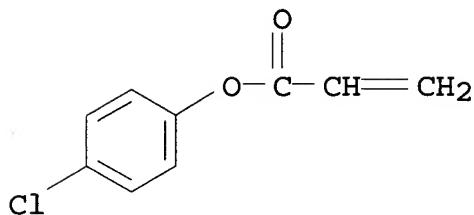
CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

CCI PMS



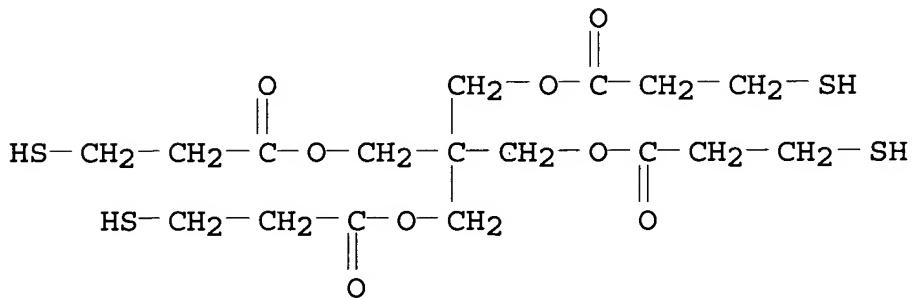
CM 3

CRN 13633-87-9
CMF C9 H7 Cl O2



CM 4

CRN 7575-23-7
CMF C17 H28 O8 S4

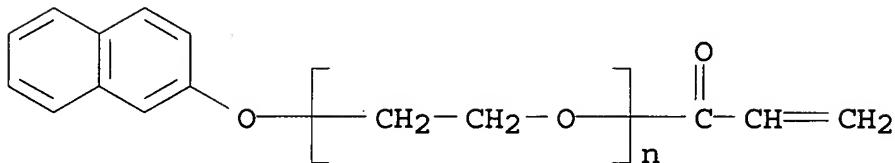


RN 773091-98-8 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) and Sanaid SI 60 (9CI) (CA INDEX NAME)

CM 1

CRN 286833-74-7
 CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂
 CCI PMS



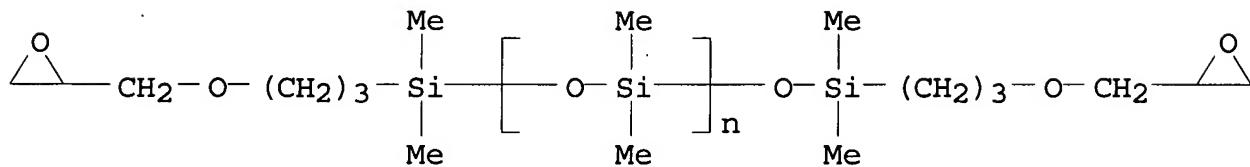
CM 2

CRN 192391-58-5
 CMF Unspecified
 CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 3

CRN 130167-23-6
 CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂
 CCI PMS



RN 773092-00-5 HCPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with 3-ethyl-3-(phenoxyethyl)oxetane, α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) and Sanaid SI 20 (9CI) (CA INDEX NAME)

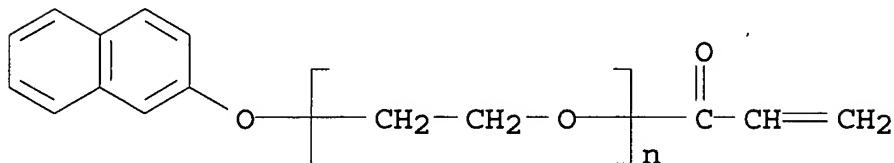
CM 1

CRN 773080-63-0
 CMF Unspecified
 CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

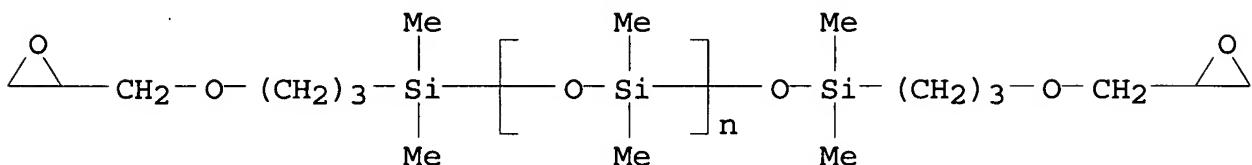
CM 2

CRN 286833-74-7
 CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂
 CCI PMS



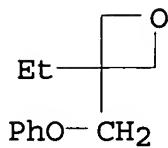
CM 3

CRN 130167-23-6
 CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂
 CCI PMS



CM 4

CRN 3897-65-2
 CMF C₁₂ H₁₆ O₂



RN 773092-01-6 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl), 3,3'-[oxybis(methylene)]bis[3-ethyloxetane] and Sanaid SI 20 (9CI) (CA INDEX NAME)

CM 1

CRN 773080-63-0

CMF Unspecified

CCI MAN

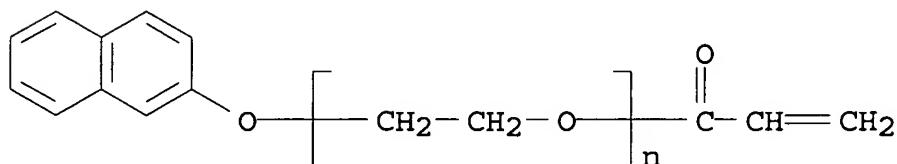
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 286833-74-7

CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂

CCI PMS

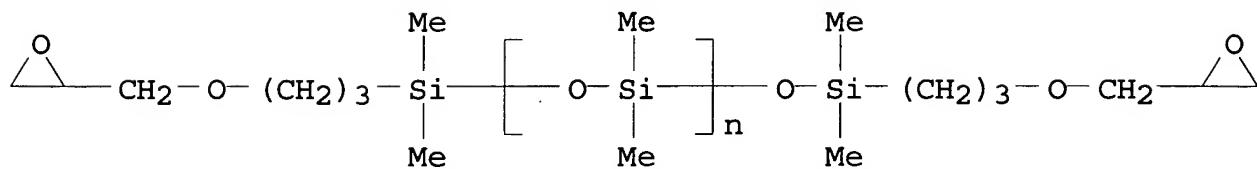


CM 3

CRN 130167-23-6

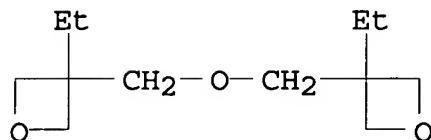
CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

CCI PMS



CM 4

CRN 18934-00-4
 CMF C12 H22 O3



RN 773092-02-7 HCPLUS
 CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with 3-ethyl-3-[(2-ethylhexyl)oxy]methyl]oxetane, α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl) and Sanaid SI 20 (9CI) (CA INDEX NAME)

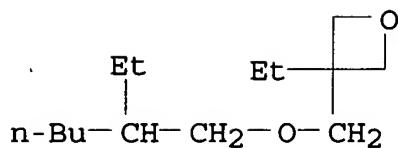
CM 1

CRN 773080-63-0
 CMF Unspecified
 CCI MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

CRN 298695-60-0
 CMF C14 H28 O2

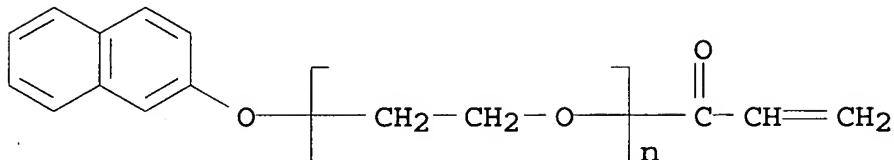


CM 3

CRN 286833-74-7

CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂

CCI PMS

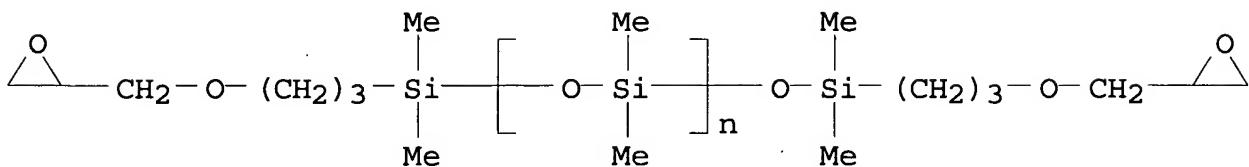


CM 4

CRN 130167-23-6

CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂

CCI PMS



RN 773092-03-8 HCPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]-, polymer with α -(1-oxo-2-propenyl)- ω -(2-naphthalenyloxy)poly(oxy-1,2-ethanediyl), 3,3'-(1,4-phenylenebis(methyleneoxymethylene))bis[3-ethyloxetane] and Sanaid SI 20 (9CI) (CA INDEX NAME)

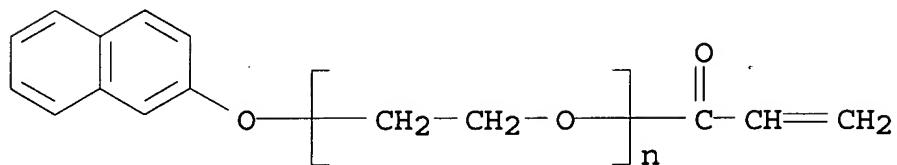
CM 1

CRN 773080-63-0
 CMF Unspecified
 CCI MAN

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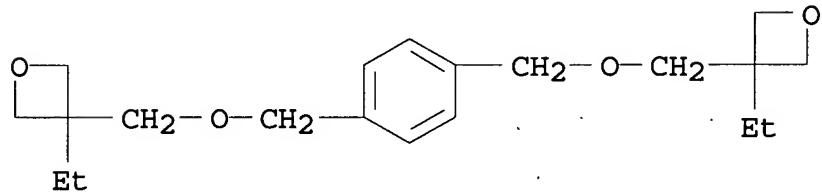
CM 2

CRN 286833-74-7
 CMF (C₂ H₄ O)_n C₁₃ H₁₀ O₂
 CCI PMS



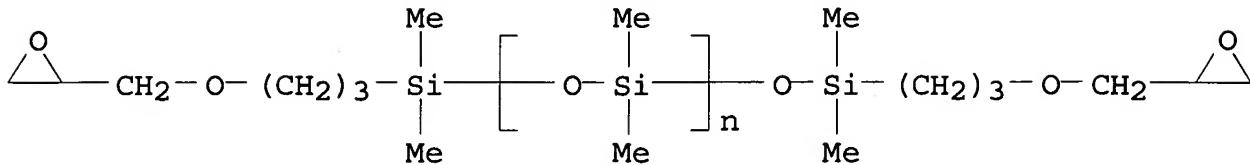
CM 3

CRN 142627-97-2
 CMF C₂₀ H₃₀ O₄



CM 4

CRN 130167-23-6
 CMF (C₂ H₆ O Si)_n C₁₆ H₃₄ O₅ Si₂
 CCI PMS



IC ICM G03H001-04
 NCL 430001000; 430002000; 359003000; 430281100
 CC 74-8 (Radiation Chemistry, **Photochemistry**, and
 Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38
 ST holog **recording** medium polymer photoinitiator
 IT Holographic **recording** materials
 (holog. **recording** medium and **recording**
 method)
 IT Polyoxyalkylenes, preparation
 (holog. **recording** medium and **recording**
 method)
 IT 13633-87-9DP, 4-Chlorophenyl acrylate, reaction products with
 diisocyanate-end polypropyleneglycol and α, ω -dihydroxy
 polypropyleneglycol 25322-69-4DP, Polypropyleneglycol,
 diisocyanate-end, reaction products with chlorophenyl acrylate
 and
 diisocyanate-end polypropyleneglycol 25322-69-4DP,
 Polypropyleneglycol, diisocyanate-end, reaction products with
 chlorophenyl acrylate and α, ω -dihydroxy
 polypropyleneglycol 771534-33-9P, Propylene glycol diglycidyl
 ether-pentaerythritol mercaptopropionate-4-bromostyrene copolymer
 771534-34-0P, Propylene glycol diglycidyl ether-pentaerythritol
 mercaptopropionate-4-chlorophenyl acrylate copolymer
 771534-35-1P 773081-54-2P 773091-90-0P
 773091-91-1P 773091-92-2P 773091-93-3P
 773091-94-4P 773091-95-5P 773091-96-6P
 773091-97-7P 773091-98-8P 773091-99-9P
 773092-00-5P 773092-01-6P 773092-02-7P
 773092-03-8P
 (holog. **recording** medium and **recording**
 method)
 IT 303110-70-5 773058-26-7 773058-27-8 773058-28-9
 773058-29-0 773058-30-3 773058-32-5 773058-34-7
 773058-37-0 773058-38-1 773058-39-2 773058-41-6
 (photopolymer. initiator; holog. **recording** medium and
recording method)

ACCESSION NUMBER: 2004:508030 HCPLUS
 DOCUMENT NUMBER: 141:79425
 TITLE: Formation of pixel elements of color filters,
 ribbed substrates, and rib-forming
 compositions therefor
 INVENTOR(S): Uraki, Hisashi; Fukuchi, Yoshihisa
 PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 20 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----	-----
	-----	-----	-----	-----
	JP 2004177948	A2	20040624	JP 2003-379531

2003

1110

PRIORITY APPLN. INFO.: JP 2002-326318 A

2002

1111

AB The compns. contain (0.01-10%) vinyl polymers containing ethylenically

unsatd. double bonds and polyorganosiloxane chains and optionally photopolymer. initiators. The compns. form barrier ribs which suppress color mixing or blurring of pixel-forming inks on jet printing.

IT 709649-40-1P

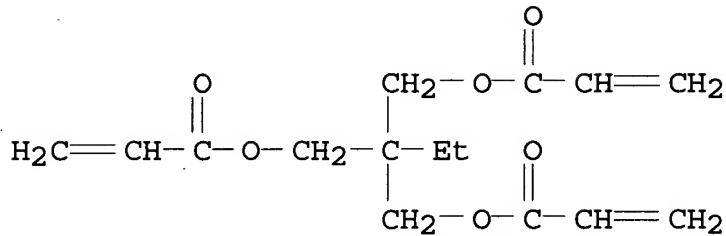
(formation of pixel elements of color filters forming siloxane polymer-containing rib patterns)

RN 709649-40-1 HCPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and oxiranylmethyl 2-methyl-2-propenoate, 2-propenoate, graft, polymer

with 2-ethyl-2-[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate (9CI) (CA INDEX NAME)

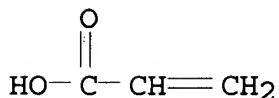
CM 1

CRN 15625-89-5
CMF C15 H20 O6

CM 2

CRN 709649-39-8
CMF (C8 H14 O2 . C7 H10 O3 . (C2 H6 O Si)n C12 H26 O3 Si2)x . x
C3 H4 O2

CM 3

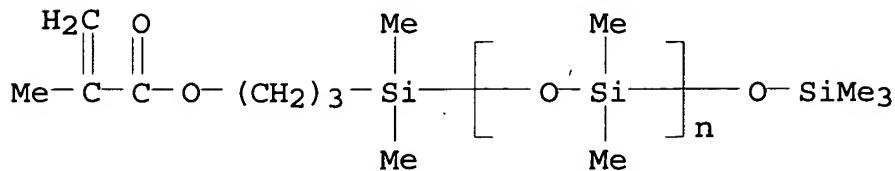
CRN 79-10-7
CMF C3 H4 O2

CM 4

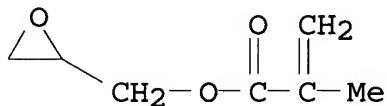
CRN 657393-71-0
CMF (C8 H14 O2 . C7 H10 O3 . (C2 H6 O Si)n C12 H26 O3 Si2)x
CCI PMS

CM 5

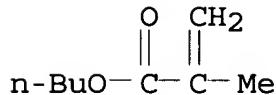
CRN 123109-42-2
CMF (C2 H6 O Si)n C12 H26 O3 Si2
CCI PMS



CM 6

CRN 106-91-2
CMF C7 H10 O3

CM 7

CRN 97-88-1
CMF C8 H14 O2

IC ICM G02B005-20

ICS C08F008-00; C08F290-06; B41J002-01

CC 74-13 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 73IT 868-77-9DP, 2-Hydroxyethyl methacrylate, reaction products with
isocyanato-bearing graft copolymers, polymers with
trimethylolpropane trimethacrylate 56793-67-0P, Butyl
methacrylate-methacrylic acid-methyl methacrylate-styrene
copolymer 657393-70-9DP, reaction products with hydroxyethyl
methacrylate, polymer with trimethylolpropane trimethacrylate
709632-98-4DP, trimethylsilyl-terminated, reaction products with
hydroxyethyl methacrylate, polymer with trimethylolpropane
trimethacrylate 709649-27-4P, Butyl methacrylate-2-hydroxyethyl
methacrylate-Silaplane FM 0721 graft copolymer ester with
isophorone diisocyanate 2-hydroxyethyl acrylate adduct (1:1),

polymer wth NK Ester ATMPT 709649-38-7DP, trimethylsilyl ether
709649-40-1P 709649-43-4DP, trimethylsilyl terminated
 (formation of pixel elements of color filters forming siloxane
 polymer-containing rib patterns)

L37 ANSWER 9 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2004:118493 HCAPLUS
 DOCUMENT NUMBER: 140:190067
 TITLE: Photosensitive composition for manufacturing
 color filter barrier wall of display using
 ink jet printing
 INVENTOR(S): Uraki, Hisashi; Fukuchi, Yoshihisa
 PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	----	-----	-----
	-----	-----	-----	-----
	JP 2004045910	A2	20040212	JP 2002-205040

2002

0715

PRIORITY APPLN. INFO.: JP 2002-205040

2002

0715

AB The title photosensitive composition comprises (A) a vinyl polymer
 containing a crosslinking group and polyorganosiloxane chain,
 and (B)
 a vinyl polymer containing a crosslinking group. The
 crosslinking
 group is hydroxy, carboxyl, isocyano, and/or epoxy. The
 composition
 may further contain a photoinitiator.
 IT **657393-71-0P**, Butyl methacrylate-glycidyl
 methacrylate-Silaplane FM 0721 graft copolymer
 (photosensitive composition for manufacturing color filter
 barrier wall of

display using ink jet printing)

RN 657393-71-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
 ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and
 oxiranylmethyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX

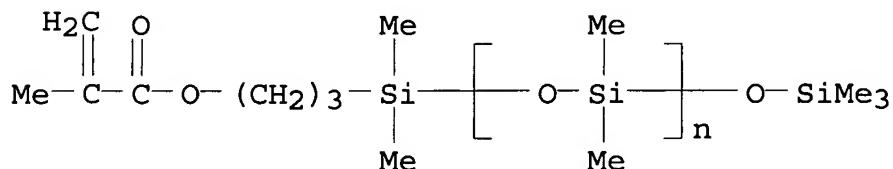
NAME)

CM 1

CRN 123109-42-2

CMF (C₂ H₆ O Si)_n C₁₂ H₂₆ O₃ Si₂

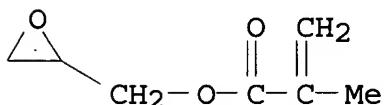
CCI PMS



CM 2

CRN 106-91-2

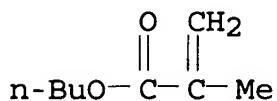
CMF C₇ H₁₀ O₃



CM 3

CRN 97-88-1

CMF C₈ H₁₄ O₂



IC ICM G02B005-20

ICS G02F001-1335

CC 74-13 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 42, 73

ST photosensitive compn color filter barrier wall **ink**
jet printing

IT **Inks**
(**jet**-printing; photosensitive composition for manufacturing color filter barrier wall of display using **ink**
jet printing)

IT Polysiloxanes, preparation
(methacrylate-, graft; photosensitive composition for manufacturing color
filter barrier wall of display using **ink** **jet**
printing)

IT **Ink-jet** printing
Optical filters
Optical imaging devices
Photoresists
(photosensitive composition for manufacturing color filter barrier wall of
display using **ink** **jet** printing)

IT 56793-67-0P, Butyl methacrylate-methacrylic acid-methyl methacrylate-styrene copolymer 657393-69-6P, Butyl methacrylate-2-hydroxyethyl methacrylate-Silaplane FM 0721 graft copolymer 657393-70-9P, Butyl methacrylate-2-(methacryloyloxy)ethyl isocyanate-Silaplane FM 0721 graft copolymer 657393-71-0P, Butyl methacrylate-glycidyl methacrylate-Silaplane FM 0721 graft copolymer
(photosensitive composition for manufacturing color filter barrier wall of
display using **ink** **jet** printing)

L37 ANSWER 10 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2004:97722 HCPLUS
DOCUMENT NUMBER: 140:129937
TITLE: Ink compositions for marking pens for **recording** materials
INVENTOR(S): Fujiwara, Yoshito
PATENT ASSIGNEE(S): Mitsubishi Pencil Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 10 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----	-----
	JP 2004035823	A2	20040205	JP 2002-197415
2002				
0705				
PRIORITY APPLN. INFO.:				JP 2002-197415
2002				
0705				
AB	The ink compns., having surface tension ≤ 22 mN/m at 25° and showing smooth writability on substrates (e.g., labels of CD-R disks), contain colorants, solvents containing C ≤ 4 aliphatic alcs. and C ≤ 6 glycol derivs., styrene-acrylic acid copolymer (I) and/or styrene- α -methylstyrene-acrylic acid copolymer, and polyoxyalkylene -modified polysiloxanes (HLB 1-14). Thus, an ink contained Valifast Black 3820 10.0, I (Joncryl 67) 3.0, propylene glycol monomethyl ether 53.9, EtOH 30.0, benzyl alc. 3.0, and polyoxyalkylene -modified polysiloxane (L 720, HLB 7) 0.1 part.			
IC	ICM C09D011-16			
CC	42-12 (Coatings, Inks, and Related Products)			
ST	polyoxylalylene polysiloxane marking ink recording material; acrylic styrene copolymer marking ink; surface tension marking ink surfactant writability			
IT	Polyoxyalkylenes , uses (di-Me polysiloxane -, Silwet FZ 2122; ink compns. for marking pens for recording materials)			
IT	Polysiloxanes , uses (di-Me, 3-hydroxypropyl Me, ethers with polyethylene-polypropylene glycol mono-Bu ether, Silwet L 720; ink compns. for marking pens for recording materials)			
IT	Polysiloxanes , uses (di-Me, polyoxyalkylene -, Silwet FZ 2122; ink compns. for marking pens for recording materials)			
IT	Optical recording materials (ink compns. for marking pens for recording materials)			

IT Inks
 (marking; ink compns. for marking pens for **recording** materials)
 IT Surfactants
 (**polyoxyalkylene-polysiloxanes**; ink compns. for marking pens for **recording** materials)
 IT **Polysiloxanes**, uses
 (**polyoxyethylene**-, Silwet FZ 2104, Silwet FZ 2191; ink compns. for marking pens for **recording** materials)
 IT 52831-04-6, Styrene- α -methylstyrene-acrylic acid copolymer
 (Joncryl 682; ink compns. for marking pens for **recording** materials)
 IT 25085-34-1, Joncryl 67
 (Joncryl 690; ink compns. for marking pens for **recording** materials)

L37 ANSWER 11 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2003:568630 HCAPLUS
 DOCUMENT NUMBER: 139:140985
 TITLE: Curable epoxy resin composition, surface
 modification process, **ink-jet recording** head and
ink-jet recording apparatus
 INVENTOR(S): Shimomura, Akihiko; Noguchi, Hiromichi;
 Imamura, Isao
 PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
 SOURCE: Eur. Pat. Appl., 24 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----	-----
	-----	-----	-----	-----
	EP 1329472	A1	20030723	EP 2003-885

2003

0115

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,
 MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ,
 EE, HU, SK

CN 1432600 A 20030730 CN 2003-100277

2003

0110

JP 2003277472 A2 20031002 JP 2003-3825

2003

0110

US 2003170401 A1 20030911 US 2003-341373

2003

0114

PRIORITY APPLN. INFO.: JP 2002-8441 A

2002

0117

AB The title composition comprises (i) a first epoxy resin having ≥ 1 water-repellency-imparting group and ≥ 2 cyclic aliphatic epoxy groups, and having Mn 8000-22,000 and polydispersity 3.5-5.0, (ii) a second epoxy resin having ≥ 1 water-repellency-imparting group and ≥ 2 cyclic aliphatic epoxy groups, having Mn 2500-8000 and polydispersity 1.5-3.0, and (iii) a cationic polymerization catalyst. The composition is useful for surface

treatment to impart water repellency or ink repellency to an article surface, especially for forming coating in a pattern by UV irradiation

IT 473272-74-1

(water-repellent; epoxy resin composition for surface modification

of ink-jet recording head and
ink-jet recording apparatus)

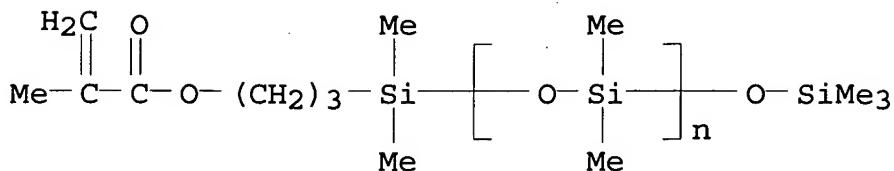
RN 473272-74-1 HCPLUS

CN 2-Propenoic acid, 2-methyl-, 7-oxabicyclo[4.1.0]hept-3-ylmethyl ester, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], graft (9CI) (CA INDEX NAME)

CM 1

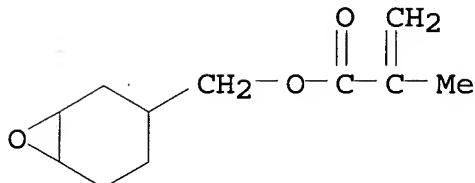
CRN 123109-42-2

CMF (C₂ H₆ O Si)_n C₁₂ H₂₆ O₃ Si₂
 CCI PMS



CM 2

CRN 82428-30-6
 CMF C₁₁ H₁₆ O₃



IC ICM C08G059-30
 ICS C08G059-32; C08G059-38; C08L063-00; B41J002-16
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 ST epoxy resin compn water repellency **ink jet recording head**
 IT Ink-jet printer heads
Ink-jet printers
 (epoxy resin composition for surface modification of **ink-jet recording head and ink-jet recording apparatus**)
 IT Epoxy resins, uses
 (water-repellent; epoxy resin composition for surface modification
 of **ink-jet recording head and ink-jet recording apparatus**)
 IT 68050-65-7, Bisphenol AF-epichlorohydrin copolymer 160099-23-0
 (compatibilizers; epoxy resin composition for surface modification
 of **ink-jet recording head and ink-jet recording apparatus**)

IT 473272-74-1 565232-42-0

(water-repellent; epoxy resin composition for surface modification

of ink-jet recording head and
ink-jet recording apparatus)REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS

AVAILABLE

IN THE RE FORMAT

L37 ANSWER 12 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2002:946891 HCAPLUS

DOCUMENT NUMBER: 138:31051

TITLE: Lithographic printing plate comprising
protective overlayerINVENTOR(S): Savariar-Hauck, Celin; Hauck, Gerhard; Frank,
Dietmar; Fiebag, Ulrich

PATENT ASSIGNEE(S): Germany

SOURCE: U.S. Pat. Appl. Publ., 13 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----	-----
	-----	-----	-----	-----
	US 2002187425	A1	20021212	US 2001-805327

2001

0313

US 6613494	B2	20030902
EP 1241003	A2	20020918
		EP 2002-5304

2002

0312

EP 1241003	A3	20031029
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR		

PRIORITY APPLN. INFO.: US 2001-805327 A

2001

0313

AB Pos.-working imageable printing plate and methods for the plate preparation are disclosed. The printing plate comprises a hydrophilic substrate; a bottom layer, which contains a pos.-working photosensitive composition; and a protective overlayer, which has an overlayer material that reduces the solubility of the photosensitive composition in an aqueous alkaline developer. The overlayer may be conveniently applied by a dip and rinse procedure. The object of the invention is to provide a printing plate that has improved photospeed but in which the unexposed regions are resistant to alkaline developers and do not require a prolonged conditioning step as part of the manufacturing process.

IC ICM G03F007-11

NCL 430272100; 430273100

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT **Polyoxyalkylenes**, uses
(Lubrimet P 900; pos.-working lithog. printing plate comprising protective overlayer)

IT **Polyethers**, uses
(di-Me siloxane-, Byk 307;
pos.-working lithog. printing plate comprising protective overlayer)

IT **Polysiloxanes**, uses
(di-Me, 3-hydroxypropyl Me, ethers with
polyethylene-polypropylene glycol
acetate, DC 190; pos.-working lithog. printing plate comprising protective overlayer)

IT **Polysiloxanes**, uses
(di-Me, polyether-, Byk 307; pos.-working
lithog. printing plate comprising protective overlayer)

IT **Polysiloxanes**, uses
(glycidyl group-containing, Edaplan LA 411; pos.-working
lithog. printing plate comprising protective overlayer)

L37 ANSWER 13 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2002:658607 HCPLUS

DOCUMENT NUMBER: 137:208403

TITLE: Method for producing ink jet

**recording head, and ink
jet recording head produced
by such method**

INVENTOR(S) : Suzuki, Toshio
 PATENT ASSIGNEE(S) : Canon Kabushiki Kaisha, Japan
 SOURCE: U.S. Pat. Appl. Publ., 18 pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	-----	-----	-----	-----
	-----	-----	-----	-----
	US 2002119248	A1	20020829	US 2002-79898

2002

0222 US 6811715 B2 20041102 JP 2001-47082 A
 PRIORITY APPLN. INFO.:

2001

0222

AB A method for producing an **ink jet
recording head**, comprises steps of forming, on a
substrate, a solid layer composed of soluble resin and having a
pattern for constituting a liquid flow path; forming an inorg.
film

by low temperature film formation so as to cover the solid layer;
forming a layer of a head forming material so as to cover the
inorg. film; removing a part of the inorg. film for forming a
discharge port; and removing the solid film thereby forming a
liquid

flow path communicating with the discharge port. An object of
the

present invention is to provide a method for producing an
ink jet recording head, capable of
avoiding peeling of the flow path forming material from the
substrate even in case of a long-sized head, and enabling
satisfactory range of material selection and satisfactory
productivity. Another object of the present invention is to
provide a method for producing an **ink jet**

recording head showing excellent durability of the hydrophilic film in the liquid flow path and of the water repellancy on the discharge port face.

IT 186294-09-7

(water-repellent resin for **ink jet recording head**)

RN 186294-09-7 HCPLUS

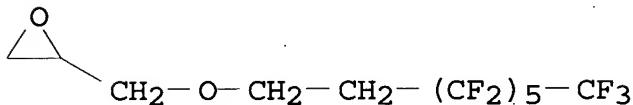
CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with (chloromethyl)oxirane, 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane and

[(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)oxy]methyl]oxirane (9CI) (CA INDEX NAME)

CM 1

CRN 122193-68-4

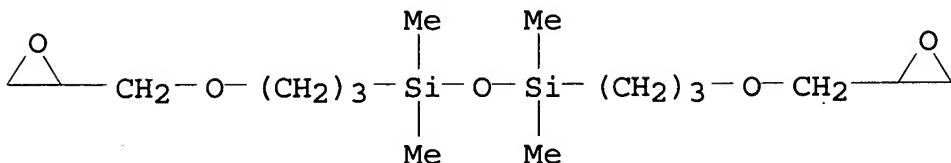
CMF C11 H9 F13 O2



CM 2

CRN 126-80-7

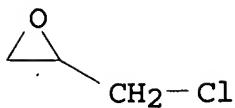
CMF C16 H34 O5 Si2



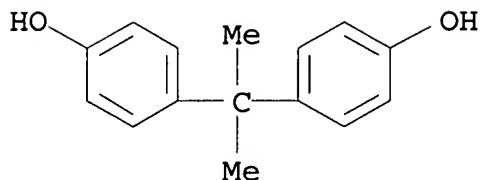
CM 3

CRN 106-89-8

CMF C3 H5 Cl O



CM 4

CRN 80-05-7
CMF C15 H16 O2

IC ICM C23C016-00
ICS B05D003-00
NCL 427248100
CC 74-6 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
ST **ink jet recording** head printer manuf
IT Vapor deposition process
(chemical; method for producing **ink jet**
recording head)
IT Sputtering
(etching, reactive; method for producing **ink**
jet recording head)
IT Ink-jet printer heads
Photoresists
Sputtering
Vapor deposition process
(method for producing **ink jet**
recording head)
IT Etching
(sputter, reactive; method for producing **ink**
jet recording head)
IT 452296-36-5, Epikote 828-Fujicure 6010 copolymer
(coating for **ink jet recording**
head)
IT 7631-86-9, Silicon oxide (SiO₂), processes
(hydrophilic film covering solid substrate of **ink**
jet recording head)
IT 132702-22-8, AZ-4903 452310-23-5, MF 58

(photoresist for **ink jet recording**
head)

IT 7440-25-7, Tantalum, uses
(substrate in **ink jet recording**
head)

IT 7429-90-5, Aluminum, uses 7440-02-0, Nickel, uses 7440-21-3,
Silicon, uses 7440-50-8, Copper, uses
(substrate of **ink jet recording**
head)

IT 186294-09-7
(water-repellent resin for **ink jet**
recording head)

REFERENCE COUNT: 23 THERE ARE 23 CITED REFERENCES AVAILABLE
FOR THIS RECORD. ALL CITATIONS

AVAILABLE
IN THE RE FORMAT

L37 ANSWER 14 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2002:503671 HCAPLUS

DOCUMENT NUMBER: 137:64382

TITLE: Elastic polyurethane foam parts and their use
in image formation devices

INVENTOR(S): Sakata, Junji; Yamazaki, Hirotaka

PATENT ASSIGNEE(S): Bridgestone Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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JP 2002187929	A2	20020705	JP 2000-388889

2000

1221	US 2002091170	A1	20020711	US 2001-985771
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2001

1106	US 6818674	B2	20041116	JP 2000-339883	A
PRIORITY APPLN. INFO.:					

2000

1108

JP 2000-388889

A

2000

1221

AB The parts with low surface friction resistance and fine cells for rollers in electrophotog. apparatus, electrostatic **recording** apparatus, etc., are obtained by (A) stirring urethane prepolymers

prepared from modified silicone oils, polyols, and polyisocyanates

with blowing agents and foam stabilizers or (B) stirring polyols, polyisocyanates, modified silicone oils, blowing agents, and foam stabilizers, wherein the modified silicone oils have polyisocyanate-reactive groups, and the foam stabilizers are silicones modified with polyethers having oxyethylene unit weight ratio 50-100%. Thus, a prepolymer prepared from ethylene oxide-propylene oxide copolymer glycerin ether, TDI, X 22-176B (alc.-modified silicone oil having 2 functional groups at one terminal) and a mixture containing conductive C, a catalyst in dipropylene glycol, and a polyether-modified silicone foam stabilizer (having polyoxyethylene content 70% in the polyether) were mixed, cast in a mold, and cured to give a conductive polyurethane foam (surface friction resistance 0.87 N), which was used to give a toner supplying roller in a dry electrophotog.

apparatus

showing good printability.

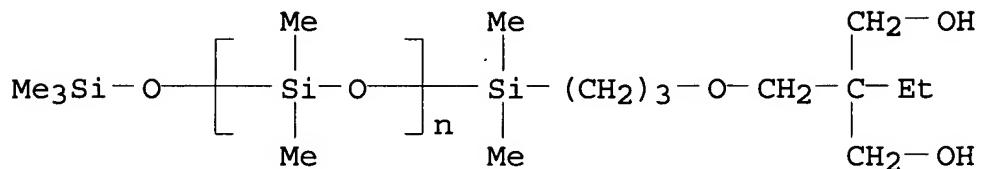
IT 439667-99-9P, Dipropylene glycol-ethylene oxide-propylene oxide copolymer glycerin ether-crude MDI-TDI-X 22-176B copolymer (elastic polyurethane foam parts and their use in image formation devices)

RN 439667-99-9 HCPLUS

CN Isocyanic acid, polymethylenepolyphenylene ester, polymer with α -[[3-[2,2-bis(hydroxymethyl)butoxy]propyl]dimethylsilyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 1,3-diisocyanatomethylbenzene, methyloxirane polymer with oxirane ether with 1,2,3-propanetriol (3:1), and oxybis[propanol] (9CI) (CA INDEX NAME)

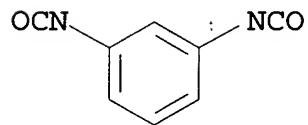
CM 1

CRN 128147-46-6
 CMF (C₂ H₆ O Si)_n C₁₄ H₃₄ O₄ Si₂
 CCI PMS



CM 2

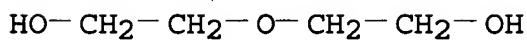
CRN 26471-62-5
 CMF C₉ H₆ N₂ O₂
 CCI IDS



D1-Me

CM 3

CRN 25265-71-8
 CMF C₆ H₁₄ O₃
 CCI IDS



2 (D1-Me)

CM 4

CRN 9016-87-9
 CMF Unspecified
 CCI PMS, MAN

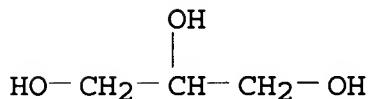
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 5

CRN 9082-00-2
 CMF C3 H8 O3 . 3 (C3 H6 O . C2 H4 O)x

CM 6

CRN 56-81-5
 CMF C3 H8 O3

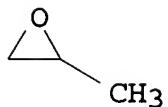


CM 7

CRN 9003-11-6
 CMF (C3 H6 O . C2 H4 O)x
 CCI PMS

CM 8

CRN 75-56-9
 CMF C3 H6 O



CM 9

CRN 75-21-8
 CMF C2 H4 O



IT 439667-98-8P, Dipropylene glycol-ethylene oxide-propylene oxide copolymer glycerin ether-TDI-X 22-176B copolymer (rubber; elastic polyurethane foam parts and their use in image formation devices)

RN 439667-98-8 HCPLUS

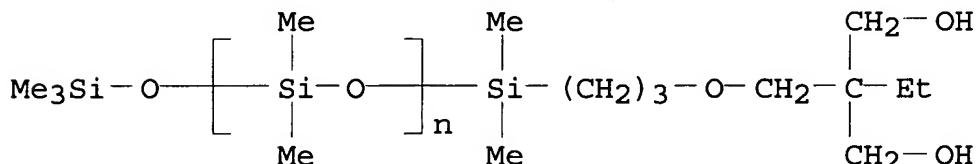
CN Propanol, oxybis-, polymer with α -[[3-[2,2-bis(hydroxymethyl)butoxy]propyl]dimethylsilyl]- ω [(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 1,3-diisocyanatomethylbenzene and methyloxirane polymer with oxirane ether with 1,2,3-propanetriol (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 128147-46-6

CMF (C₂ H₆ O Si)_n C₁₄ H₃₄ O₄ Si₂

CCI PMS

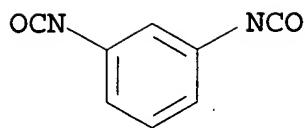


CM 2

CRN 26471-62-5

CMF C₉ H₆ N₂ O₂

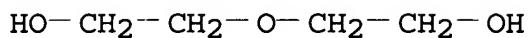
CCI IDS



D1-Me

CM 3

CRN 25265-71-8
 CMF C6 H14 O3
 CCI IDS



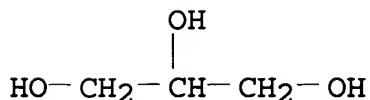
2 (D1-Me)

CM 4

CRN 9082-00-2
 CMF C3 H8 O3 . 3 (C3 H6 O . C2 H4 O)x

CM 5

CRN 56-81-5
 CMF C3 H8 O3



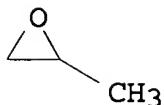
CM 6

CRN 9003-11-6

CMF (C₃ H₆ O . C₂ H₄ O)x
 CCI PMS

CM 7

CRN 75-56-9
 CMF C₃ H₆ O



CM 8

CRN 75-21-8
 CMF C₂ H₄ O



IC ICM C08G018-61
 ICS F16C013-00; G03G015-02; G03G015-08; G03G015-16; C08G018-61;
 C08G101-00
 CC 39-9 (Synthetic Elastomers and Natural Rubber)
 Section cross-reference(s): 74
 IT 439667-99-9P, Dipropylene glycol-ethylene oxide-propylene
 oxide copolymer glycerin ether-crude MDI-TDI-X 22-176B copolymer
 (elastic polyurethane foam parts and their use in image
 formation devices)
 IT 9082-00-2DP, Ethylene oxide-propylene oxide copolymer glycerin
 ether, polymers with TDI and alc.-modified silicones
 26471-62-5DP, TDI, polymers with polyether polyols and
 alc.-modified silicones 439667-98-8P, Dipropylene
 glycol-ethylene oxide-propylene oxide copolymer glycerin
 ether-TDI-X 22-176B copolymer
 (rubber; elastic polyurethane foam parts and their use in
 image
 formation devices)

L37 ANSWER 15 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2002:10038 HCAPLUS
 DOCUMENT NUMBER: 136:55389

TITLE: Ink, ink set, ink-jet recording process, ink cartridge, recording unit and ink-jet recording apparatus
 INVENTOR(S): Osumi, Koichi; Mishina, Shinya; Teraoka, Hisashi; Yakushigawa, Yuko
 PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
 SOURCE: Eur. Pat. Appl., 36 pp.
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	EP 1167474	A1	20020102	EP 2001-115205

2001

0622

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,
 MC, PT, IE, SI, LT, LV, FI, RO

JP 2002080768	A2	20020319	JP 2001-191881
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2001

0625

US 6474804	B2	20021105	US 2001-887259
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2001

0625

PRIORITY APPLN. INFO.: JP 2000-190331 A

2000

0623

AB An ink comprises a dye, a silicon-containing surfactant, an ethylene oxide adduct of acetylene glycol and a liquid medium, wherein a weight ratio of the silicon-containing surfactant to the ethylene oxide adduct of acetylene glycol is not lower than 1/5000, but lower than 1/20. An ink-jet recording process comprises the

step of ejecting the ink by an ink-jet system. An ink set comprises in combination a first dye having a certain color tone, and a second dye ink having a color tone different from that of the first dye ink, wherein at least one of the first and second dye inks is the above ink. An ink set comprises dye inks of yellow, magenta and cyan, wherein the dye inks comprise an ethylene oxide adduct of acetylene glycol resp., and the dye inks of magenta and cyan further comprise a silicon-containing surfactant.

IC ICM C09D011-00

CC 42-12 (Coatings, Inks, and Related Products)

IT **Polysiloxanes, uses**

(FZ-2162; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Polyurethanes, uses**

(cartridge; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Polysiloxanes, uses**

(di-Me, 3-hydroxypropyl Me, ethers with **polyethylene-polypropylene glycol** mono-Bu ether, L-720; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Dyes**

Ink-jet printers

(ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Inks**

(jet-printing; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Polysiloxanes, uses**

(**polyoxyalkylene**-, FZ-2123; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Polyoxyalkylenes, uses**

(**polysiloxane**-, FZ-2123; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT **Surfactants**

(silicon-containing; ink, ink set, ink-jet **recording** process, ink cartridge, **recording** unit and ink-jet **recording** apparatus)

IT 9003-07-0, Polypropylene 9003-20-7, Polyvinyl acetate

9004-34-6, Cellulose, uses
 (cartridge; ink, ink set, ink-jet **recording** process,
 ink cartridge, **recording** unit and ink-jet
recording apparatus)

IT 9014-85-1, Acetylenol EH 12222-04-7, C.I. Direct Blue 199
 27306-78-1, Silwet L-77 50925-42-3, C.I. Direct Yellow 86
 (ink, ink set, ink-jet **recording** process, ink
 cartridge, **recording** unit and ink-jet
recording apparatus)

REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS
 AVAILABLE
 IN THE RE FORMAT

L37 ANSWER 16 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2001:565158 HCPLUS
 DOCUMENT NUMBER: 135:154154
 TITLE: Lubricating acrylic polysiloxane coating
 agents
 INVENTOR(S): Kamiya, Daisuke; Maeda, Keiji; Okazaki,
 Eiichi
 PATENT ASSIGNEE(S): Toagosei Co., Ltd., Japan
 SOURCE: PCT Int. Appl., 27 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
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	-----	-----	-----	-----
	WO 2001055272	A1	20010802	WO 2001-JP350

2001

0119

W: CN, KR, US
 RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU,
 MC, NL, PT, SE, TR
 JP 2001279165 A2 20011010 JP 2000-149335

2000

0522

PRIORITY APPLN. INFO.: JP 2000-15140 A

2000

0125

JP 2000-149335

A

2000

0522

AB Title agents, useful as antisticking backings of thermal-transfer **recording** films, are polymers consisting of silicone units 0.5-60, cyclic imido units 5-99, and other monomer-based units 0.5-94.5%. A MEK solution containing 30:40:30 Me methacrylate-tetrahydrophthalimidoethyl acrylate-X 22 174DX copolymer was spread on a polyester film and UV-cured to form a film showing dynamic friction 0.030 μ k and releasing ability 19 N/m and resulting good prints in thermal-transfer printing.

IT 352239-21-5P

(imido acrylate polysiloxane coatings as antisticking backings for thermal-transfer **recording** films)

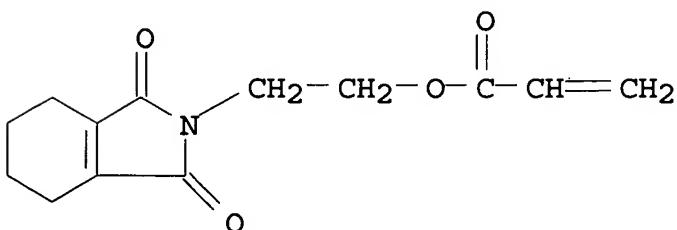
RN 352239-21-5 HCPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 2-(1,3,4,5,6,7-hexahydro-1,3-dioxo-2H-isoindol-2-yl)ethyl 2-propenoate, methyl 2-methyl-2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

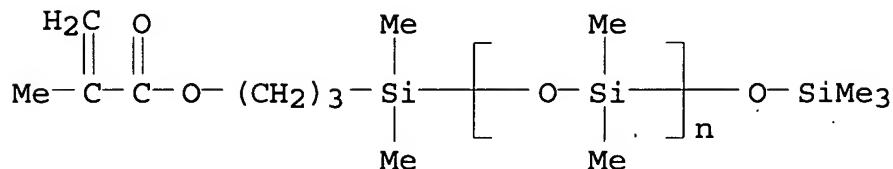
CRN 125350-99-4

CMF C13 H15 N O4



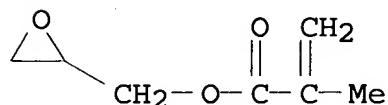
CM 2

CRN 123109-42-2
 CMF (C₂ H₆ O Si)_n C₁₂ H₂₆ O₃ Si₂
 CCI PMS



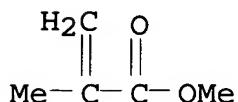
CM 3

CRN 106-91-2
 CMF C₇ H₁₀ O₃



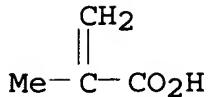
CM 4

CRN 80-62-6
 CMF C₅ H₈ O₂



CM 5

CRN 79-41-4
 CMF C₄ H₆ O₂



IC C09D183-04; C09D135-00; C09D133-06; C09D004-06; B41M005-40
 CC 42-10 (Coatings, Inks, and Related Products)
 Section cross-reference(s): 74
 IT Polysiloxanes, uses
 (acrylic; imido acrylate polysiloxane coatings as antisticking
 backings for thermal-transfer **recording** films)
 IT Coating materials
 (blocking-resistant; imido acrylate polysiloxane coatings as
 antisticking backings for thermal-transfer **recording**
 films)
 IT Thermal-transfer printing materials
 (sheets; imido acrylate polysiloxane coatings as antisticking
 backings for thermal-transfer **recording** films)
 IT 352239-18-0P 352239-19-1P 352239-20-4P **352239-21-5P**
 352270-56-5P
 (imido acrylate polysiloxane coatings as antisticking backings
 for thermal-transfer **recording** films)

REFERENCE COUNT: 12 THERE ARE 12 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS

AVAILABLE

IN THE RE FORMAT

L37 ANSWER 17 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 2001:189208 HCPLUS
 DOCUMENT NUMBER: 134:214917
 TITLE: Removing agent composition for photoresist
 INVENTOR(S): Paek, Chiheun; Oh, Changi; Lee, Sangdae; Jin,
 Yuanlai; Liu, Zhongshun
 PATENT ASSIGNEE(S): Tongjin Chemical Industry Co., Ltd., S. Korea
 SOURCE: Faming Zhanli Shenqing Gongkai Shuomingshu,
 32 pp.
 DOCUMENT TYPE: CODEN: CNXXEV
 LANGUAGE: Patent
 FAMILY ACC. NUM. COUNT: Chinese
 PATENT INFORMATION: 1

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----
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CN 1258730 A 20000705 CN 1999-118360

1999

0830

CN 1118003 B 20030813
KR 2000046480 A 20000725 KR 1998-63166

1998

1231

TW 575782 B 20040211 TW 1999-88113365

1999

0805

US 6140027 A 20001031 US 1999-435569

1999

1108

PRIORITY APPLN. INFO.: KR 1998-63166 A

1998

1231

AB This patent disclosed a photoresist removing agent composition comprising: (1) 10-40 weight% water-soluble amine compound, (2) 20-50 weight% polar organic solvent selected from DMSO, N-methylpyrrolidone (NMP), di-Me acetamide (DMA), DMF and di-Me imidazolidinone (DMI), (3) 10-30 weight% water, (4) 0.1-10 weight% polyhydroxy phenol compound, (5) 0.1-10% triazole compound, and (6) 0.01-1 weight% polysiloxane surfactant. The composition can easily remove photoresist layer with min. corrosion on metal substrate.

IC ICM C11D001-82

ICS C11D003-32; H05K003-26

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 76

IT **Polysiloxanes**, uses

(di-Me, 3-hydroxypropyl Me, ethers with
polyethylene-polypropylene glycol
 mono-Bu ether, L 720; surfactant in photoresist removing agent
 composition)

IT **Polysiloxanes**, uses
 (di-Me, 3-hydroxypropyl Me, ethoxylated
 propoxylated, L 7230; surfactant in photoresist removing agent
 composition)

IT **Polyoxyalkylenes**, uses
 (di-Me, Me hydrogen **polysiloxane**
 -, L 7600; surfactant in photoresist removing agent
 composition)

IT **Polysiloxanes**, uses
 (di-Me, Me hydrogen,
polyoxyalkylene-, L 7600; surfactant in photoresist
 removing agent composition)

IT **Polysiloxanes**, uses
 (di-Me, hydroxypropyl Me, ethers with
polyoxyalkylene glycol mono-C1-3-alkyl ether, L 7604;
 surfactant in photoresist removing agent composition)

IT **Polysiloxanes**, uses
 (ethoxylated, L 7614; surfactant in photoresist removing agent
 composition)

IT 67-68-5, DMSO, uses 68-12-2, DMF, uses 80-73-9
 872-50-4, NMP, uses
 (polar solvent in photoresist removing agent composition).

L37 ANSWER 18 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2000:511793 HCPLUS

DOCUMENT NUMBER: 133:142575

TITLE: Developer for electrophotographic development
 and **ink-jet** printing and
 recording material such as **ink**
 therefor

INVENTOR(S): Tsubushi, Kazuo; Asami, Takeshi; Ishikawa,
 Aiko

PATENT ASSIGNEE(S): Ricoh Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 14 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----

JP 2000206738 A2 20000728 JP 1999-3488

1999

0108 US 2002081515 A1 20020627 US 2001-943448

2001

0830 US 2003065064 A1 20030403 US 2002-170910

2002

0612 US 6620569 B2 20030916
US 2004010075 A1 20040115 US 2003-613544

2003

0702 PRIORITY APPLN. INFO.: JP 1999-3488 A

1999

0108 US 1999-472575 B1

1999

1227 / US 2001-943448 B1

2001

0830 US 2002-170910 A3

2002

0612

AB The invention relates to a developer used in electrophotog.

development or in **ink-jet** printing has a toner, which contains a colorant and a resin, or **ink** in an insulative carrier solution, wherein the developer contains a reactive silicone compound. The addition of the silicone compound enables

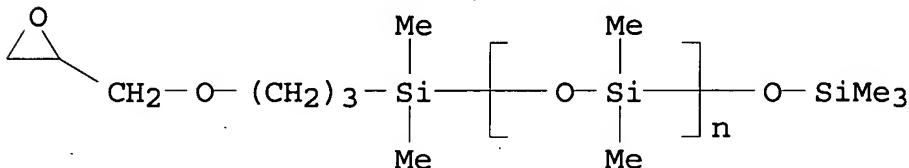
the developer suitable for use with a high-b.p. carrier solution

IT 157723-26-7, FM 0511

(FM 0511; developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

RN 157723-26-7 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[(trimethylsilyl)oxy]- (9CI) (CA INDEX NAME)



IC ICM G03G009-12

ICS C09D011-00; G03G009-13

CC 74-3 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

ST developer electrophotog **ink jet** printing

IT Polysiloxanes, uses

(developer for electrophotog. development and **ink-jet** printing)

IT Electrophotographic developers

(developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

IT Polysiloxanes, uses

(di-Me, di-Ph, [(ethenyldimethylsilyl)oxy]-terminated, FP

2231;

developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

IT Polysiloxanes, uses

(methacrylate-, X 22-5502; developer for electrophotog. development and **ink-jet** printing and **recording** material such as **ink**)

IT 157723-26-7, FM 0511

(FM 0511; developer for electrophotog. development and

ink-jet printing and recording
material such as ink)
IT 115254-29-0, FM 1111
(FM 1111; developer for electrophotog. development and
ink-jet printing and recording
material such as ink)
IT 26403-67-8, KF 99 42557-10-8, KF 96-100 156048-34-9D,
ethenyldimethylsilyl terminated 156327-07-0, FM 4421
(developer for electrophotog. development and ink-
jet printing and recording material such as
ink)

L37 ANSWER 19 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2000:312492 HCPLUS
DOCUMENT NUMBER: 133:51072
TITLE: Epoxy Resin-Photopolymer Composites for
Volume Holography
AUTHOR(S): Trentler, Timothy J.; Boyd, Joel E.; Colvin,
Vicki L.
CORPORATE SOURCE: Department of Chemistry, Rice University,
Houston, TX, 77005, USA
SOURCE: Chemistry of Materials (2000), 12(5),
1431-1438
CODEN: CMATEX; ISSN: 0897-4756
PUBLISHER: American Chemical Society
DOCUMENT TYPE: Journal
LANGUAGE: English
AB Efficient materials for recording volume holograms are
described that could potentially find application in archival
data storage. These materials are prepared by mixing
photopolymerizable
vinyl monomers with a liquid epoxy resin and an amine hardener.

A solid matrix is formed in situ as the epoxy cures at room
temperature
The unreacted vinyl monomers are subsequently photopolymerized during
hologram recording. A key feature of these materials is
the separation of the epoxy and vinyl polymers. This separation
allows for a
large index contrast to be developed in holograms when components
are optimized. The standard material described in this work
consists
of a low index matrix (n equivalent 1.46), comprised of
diethylenetriamine and 1,4-butanediol diglycidyl ether, and a
high

index photopolymer mixture (n equivalent 1.60) of N-vinylcarbazole and

N-vinyl-2-pyrrolidinone. This material is functional in thick formats (several millimeters), which enables narrow angular bandwidth and high diffraction efficiency. A dynamic range (M/#) up to 13 has been measured in these materials. Holog. performance

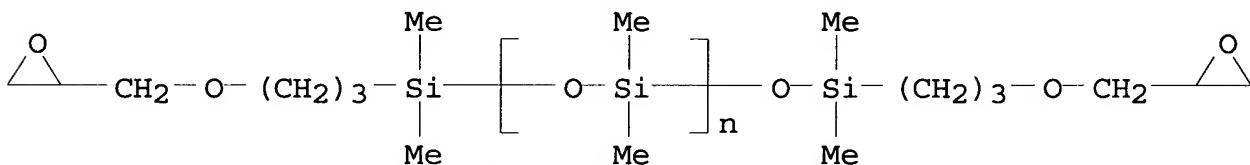
is highly dependent on the amount of amine hardener used, as well as on photopolymer shrinkage.

IT 130167-23-6

(holog. **recording** material mixture containing photopolymerizable vinyl monomers and epoxy resin matrix produced by curing composition containing)

RN 130167-23-6 HCAPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy] - (9CI) (CA INDEX NAME)



CC 74-8 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

ST holog **recording** material epoxy resin photopolymerizable monomer composite; vinyl photopolymerizable monomer epoxy resin matrix holog **recording**

IT Polyamines

Polyamines

Polyamines

(epoxy-polyether-; holog. **recording** material containing photopolymerizable vinyl monomers and epoxy resin matrix)

IT Holographic **recording** materials

(holog. **recording** material containing photopolymerizable vinyl monomers and epoxy resin matrix)

IT Polymerization

(photopolymn.; holog. **recording** material containing photopolymerizable vinyl monomers and epoxy resin matrix)

IT Polyethers, uses

Polyethers, uses

Polyethers, uses

(polyamine-epoxy-; holog. **recording** material containing

photopolymerizable vinyl monomers and epoxy resin matrix)

IT Epoxy resins, uses
 Epoxy resins, uses
 Epoxy resins, uses
 (polyamine-polyether-; holog. **recording** material
 containing photopolymerizable vinyl monomers and epoxy resin
 matrix)

IT 30112-03-9, N-Vinylcarbazole-N-Vinyl-2-pyrrolidinone copolymer
 (holog. **recording** in material containing
 photopolymerizable vinyl monomers and epoxy resin matrix)

IT 75-91-2, Tert-Butylhydroperoxide
 (holog. **recording** in material containing
 photopolymerizable vinyl monomers and epoxy resin matrix)

IT 88-12-0, N-Vinyl-2-pyrrolidinone, reactions 1484-13-5,
 N-Vinylcarbazole
 (holog. **recording** material containing photopolymerizable
 vinyl monomers and epoxy resin matrix)

IT 78811-10-6, 1,4-Butanediol diglycidyl ether-diethylenetriamine
 copolymer 153972-09-9, Bis(4-glycidyloxyphenyl)methane-m-
 xylenediamine copolymer 238752-94-8, 1,2,7,8-Diepoxyoctane-
 diethylenetriamine copolymer
 (holog. **recording** material containing photopolymerizable
 vinyl monomers and epoxy resin matrix)

IT 111-40-0, Diethylenetriamine 1477-55-0, m-Xylenediamine
 2095-03-6, Bis(4-glycidyloxyphenyl)methane 2425-79-8,
 1,4-Butanediol diglycidyl ether 2426-07-5,
 1,2,7,8-Diepoxyoctane
130167-23-6
 (holog. **recording** material mixture containing
 photopolymerizable vinyl monomers and epoxy resin matrix
 produced by curing composition containing)

IT 125051-32-3, Irgacure 784
 (photoinitiator; holog. **recording** in material containing
 photopolymerizable vinyl monomers and epoxy resin matrix)

REFERENCE COUNT: 47 THERE ARE 47 CITED REFERENCES AVAILABLE
 FOR THIS RECORD. ALL CITATIONS

AVAILABLE

IN THE RE FORMAT

L37 ANSWER 20 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1999:679933 HCPLUS

DOCUMENT NUMBER: 131:315851

TITLE: **Recording** material for aqueous
 ink and its manufacture

INVENTOR(S): Kuwahara, Shoji; Yoshikawa, Takeshi;
 Nakagami,
 Yoshiaki

PATENT ASSIGNEE(S) : Toyo Ink Mfg. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF

DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
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JP 11291613	A2	19991026	JP 1998-100728

1998

0413

PRIORITY APPLN. INFO.: JP 1998-100728

1998

0413

AB The title **recording** material comprises an **ink**-receiving layer formed on at least one side of a support, wherein the **ink**-receiving layer has microvoids on the surface and contains a water-absorbing polyurethane-polyurea 60.0-99.9 and dimethylpolysiloxane-modified acrylic resin 0.1-40.0%. The process comprises drying the **ink**-receiving layer at 50-150° after applying a coating material to form the **ink**-receiving layer on the support. The recoring material evaluated by using **ink-jet** printing and gravure printing methods provided sharp images and waterfastness.

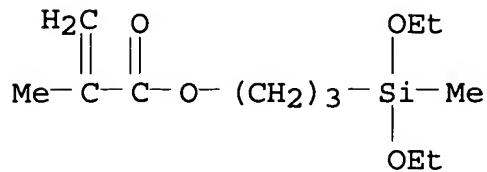
IT 247240-90-0 (ink-receiving layer of **recording** material for aqueous **ink**)

RN 247240-90-0 HCPLUS

CN 2-Propenoic acid, 2-methyl-, polymer with 3-(diethoxymethylsilyl)propyl 2-methyl-2-propenoate, α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]oxy]poly[oxy(dimethylsilylene)], ethyl 2-propenoate and oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

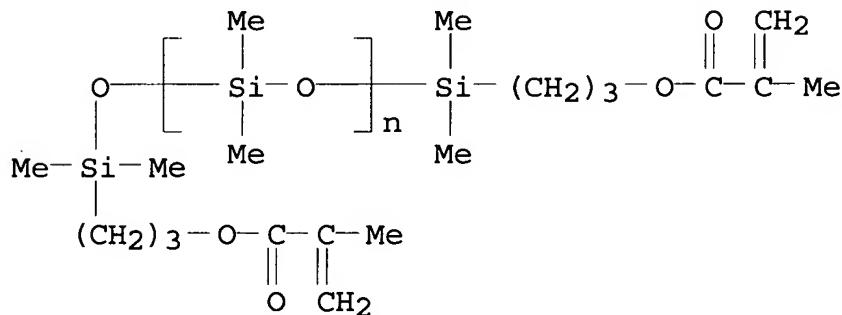
CM 1

CRN 65100-04-1
CMF C12 H24 04 Si



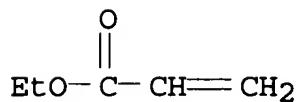
CM 2

CRN 58130-03-3
CMF (C2 H6 O Si)n C18 H34 O5 Si2
CCI PMS



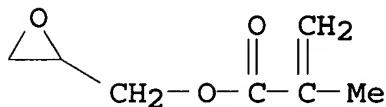
CM 3

CRN 140-88-5
CMF C5 H8 O2



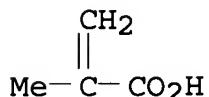
CM 4

CRN 106-91-2
 CMF C7 H10 O3



CM 5

CRN 79-41-4
 CMF C4 H6 O2



IC ICM B41M005-00
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 37, 42
 ST polyurethane polyurea aq ink recording
 material drying process
 IT Gravure printing
 Ink-jet printing
 (ink-receiving layer of recording material
 for aqueous ink)
 IT Drying
 (manufacture of ink-receiving layer of recording
 material for aqueous ink)
 IT Polyurethanes, uses
 (polyurea-; ink-receiving layer of recording
 material for aqueous ink)
 IT Polyureas
 (polyurethane-; ink-receiving layer of
 recording material for aqueous ink)
 IT 26300-51-6, Acrylic acid-butyl acrylate-methyl methacrylate
 copolymer 247240-90-0 247240-92-2 247240-94-4
 247240-96-6 247240-98-8
 (ink-receiving layer of recording material
 for aqueous ink)
 IT 201858-42-6P 201933-27-9P 247240-88-6P
 (ink-receiving layer of recording material)

for aqueous ink)

L37 ANSWER 21 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1999:648833 HCAPLUS
 DOCUMENT NUMBER: 131:279296
 TITLE: UV-curable resins, their compositions, and solder photoresist inks thereof
 INVENTOR(S): Marusawa, Takashi; Hashimoto, Soichi
 PATENT ASSIGNEE(S): Gooh Chemical Industry Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	JP 11279243	A2	19991012	JP 1998-87036

1998

0331

PRIORITY APPLN. INFO.: JP 1998-87036

1998

0331

AB The UV-curable resins have ≥ 2 ethylenically unsatd. groups, CO₂H, and Si and are prepared (i) by reacting HO₂C-containing ethylenically unsatd. monomers and (un)saturated polybasic acid anhydrides with copolymers comprising Si-containing ethylenically unsatd. monomers and epoxy-containing ethylenically unsatd. monomers or (ii) by reacting epoxy-containing ethylenically unsatd. monomers with copolymers comprising Si-containing ethylenically unsatd. monomers and HO₂C-containing ethylenically unsatd. monomers. The compns. contain the UV-curable resins and compds. with ≥ 2 epoxy groups. The solder photoresist inks contain the compns., photopolymn. initiators, and diluents. The inks can be developed using dilute alkali solns. and give solder resists having excellent resistance to solvents, acids, Ag plating, and

electrolytic corrosion.

IT **245727-49-5P**, Acrylic acid-glycidyl methacrylate-1-(3-methacryloxypropyl)polydimethylsiloxane-methyl methacrylate-tetrahydrophthalic anhydride copolymer
245727-51-9P, Acrylic acid-glycidyl methacrylate-1-(3-methacryloxypropyl)polydimethylsiloxane-methyl methacrylate-N-phenylmaleimide copolymer

(UV-curable silicon-containing acrylic polymers, their compns., and solder photoresist inks thereof)

solder photoresist inks thereof)

RN 245727-49-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
α-[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
ω-[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)],
oxiranylmethyl 2-methyl-2-propenoate, 2-propenoic acid and
3a,4,7,7a-tetrahydro-1,3-isobenzofurandione (9CI) (CA INDEX)

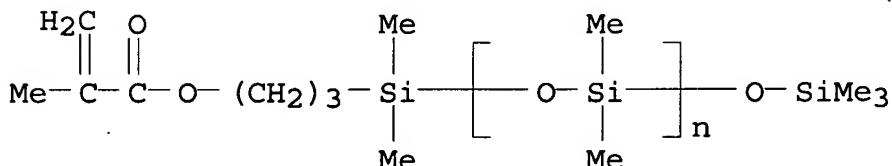
NAME)

CM 1

CRN 123109-42-2

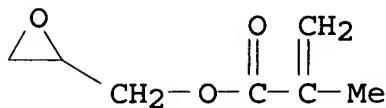
CMF (C₂ H₆ O Si)_n C₁₂ H₂₆ O₃ Si₂

CCT PMS



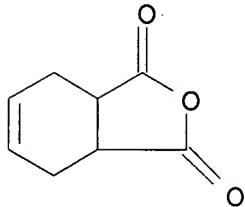
CM 2

CRN 106-91-2
CMF C7 H10 O3



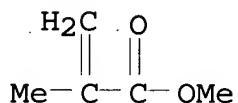
CM 3

CRN 85-43-8
 CMF C8 H8 O3



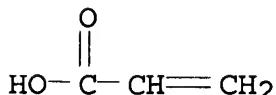
CM 4

CRN 80-62-6
 CMF C5 H8 O2



CM 5

CRN 79-10-7
 CMF C3 H4 O2

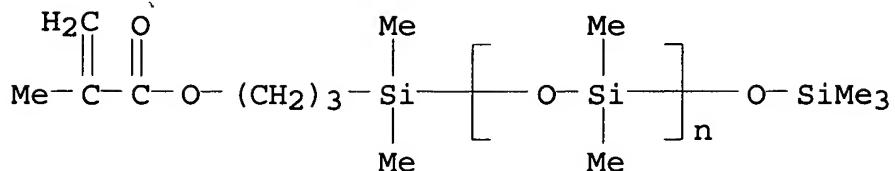


RN 245727-51-9 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
 α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
 ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)],
 oxiranylmethyl 2-methyl-2-propenoate, 1-phenyl-1H-pyrrole-2,5-dione and 2-propenoic acid (9CI) (CA INDEX NAME)

CM 1

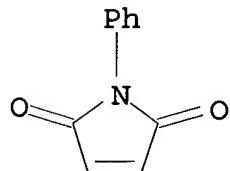
CRN 123109-42-2
 CMF (C₂ H₆ O Si)_n C₁₂ H₂₆ O₃ Si₂

CCl PMS



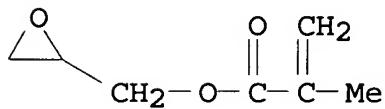
CM 2

CRN 941-69-5
 CMF C10 H7 N O2



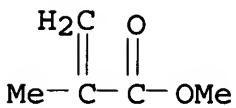
CM 3

CRN 106-91-2
 CMF C7 H10 O3

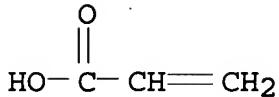


CM 4

CRN 80-62-6
 CMF C5 H8 O2



CM 5

CRN 79-10-7
CMF C3 H4 O2

IC ICM C08F299-00
 ICS C08F002-48; C08F290-04; C09D011-10; G03F007-027;
 G03F007-038;
 G03F007-075; H05K003-28; C09D004-00

CC 74-5 (Radiation Chemistry, Photochemistry, and
 Photographic and Other Reprographic Processes)
 Section cross-reference(s): 37, 38

IT Epoxy resins, uses
 (UV-curable silicon-containing acrylic polymers, their
 compns., and
 solder photoresist inks thereof)

IT Polysiloxanes, preparation
 (acrylic; UV-curable silicon-containing acrylic polymers,
 their
 compns., and solder photoresist inks thereof)

IT Solder resists
 Solder resists
 (photoresists; UV-curable silicon-containing acrylic polymers,
 their compns., and solder photoresist inks thereof)

IT Photoresists
 Photoresists
 (solder; UV-curable silicon-containing acrylic polymers, their
 compns., and solder photoresist inks thereof)

IT 245727-49-5P, Acrylic acid-glycidyl methacrylate-1-(3-
 methacryloxypropyl)polydimethylsiloxane-methyl
 methacrylate-tetrahydrophthalic anhydride copolymer
 245727-50-8P, Acrylic acid-glycidyl methacrylate-methyl
 methacrylate-tetrahydrophthalic anhydride-trimethylsilylmethyl
 methacrylate copolymer 245727-51-9P, Acrylic
 acid-glycidyl
 methacrylate-1-(3-methacryloxypropyl)polydimethylsil
 oxane-methyl methacrylate-N-phenylmaleimide copolymer
 (UV-curable silicon-containing acrylic polymers, their
 compns., and

IT 28825-96-9, TEPIC 29570-58-9 71868-10-5, Irgacure 907
 87912-85-4, Epiclon N 680 89118-70-7, YX 4000
 (UV-curable silicon-containing acrylic polymers, their
 compns., and
 solder photoresist inks thereof)

L37 ANSWER 22 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1999:648633 HCPLUS
 DOCUMENT NUMBER: 131:264821
 TITLE: Adhesive printing paper with metallic luster
 INVENTOR(S): Iguchi, Yuji; Nakajima, Toshimitsu
 PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	----	-----	-----
	-----	-----	-----	-----
	JP 11277890	A2	19991012	JP 1998-87423

1998

0331
 PRIORITY APPLN. INFO.: JP 1998-87423

1998

0331

AB The printing paper comprises on 1 side of a support an adhesive resin layer, a metal foil layer, and an ink receptor layer, and on the other side of the support a hot-melt adhesive layer. The hot-melt adhesive layer may contain a surfactant and water-soluble thermoplastics. A heat-insulator layer may be interposed between the support and the hot-melt adhesive layer. The printing paper can be adhered onto a postcard with a hot iron.
 IC ICM B41M005-00
 ICS B41M005-40; B41M005-38; G09F003-02
 CC 74-6 (Radiation Chemistry, Photochemistry, and

Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38, 43
 IT **Polyoxyalkylenes**, uses
 (PEO 1, surfactant; adhesive printing paper with metallic
 luster for making printed postcard)
 IT **Polysiloxanes**, uses
 (di-Me, 3-hydroxypropyl Me, ethers with
 polyethylene-polypropylene glycol
 mono-Me ether, Silwet L 7001, surfactant; adhesive printing
 paper with metallic luster for making printed postcard)
 IT Ink-jet **recording** sheets
 Thermal-transfer printing materials
 (paper; adhesive printing paper with metallic luster for
 making
 printed postcard)

L37 ANSWER 23 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1997:701440 HCPLUS
 DOCUMENT NUMBER: 128:28565
 TITLE: Nonagglomerating antifoamant for silver
 halide
 photographic emulsions
 INVENTOR(S): Orem, Michael William; Daubendiek, Richard
 Lee; Oehlbeck, Douglas Lee; Lighthouse,
 Joseph
 George
 PATENT ASSIGNEE(S): Eastman Kodak Co., USA
 SOURCE: U.S., 5 pp.
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
-----	-----	-----	-----

US 5681692	A	19971028	US 1996-594611

1996

0202

PRIORITY APPLN. INFO.: US 1996-594611

1996

0202

AB The invention relates to a solution for forming silver halide emulsions comprising water, gelatin containing less than 30 μmol of methionine per g of gelatin, and at least one antifoamant selected from the group consisting of $\text{RCO}_2(\text{CH}_2\text{CH}_2\text{O})_x\text{OCR}$ wherein RC and CR represent the carbon chains in carboxylic acids with chain lengths of predominantly 12-18 carbon atoms and x has a mean value of 4 to 5 from a mixture with a distribution of values between 2 and 7 and $(\text{H}_3\text{CSi})[(\text{OSi}(\text{CH}_3)_2)_d\text{O}(\text{CH}_2\text{CH}_2\text{CH}_2\text{O})_n\text{C}_4\text{H}_9]_3$ wherein the mol. weight is 2500 to 3500 and d and n have average values of less than 15.

IC ICM G03C001-043
ICS B01D019-04

NCL 430569000

CC 74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT **Polyoxyalkylenes**, uses
(di-Me, Me hydrogen polysiloxane
-, Silwet L-720; antifoamant for silver halide photog. emulsions)

IT **Polysiloxanes**, uses
(di-Me, Me hydrogen,
polyoxyalkylene-, Silwet L-720; antifoamant for silver halide photog. emulsions)

IT **Polysiloxanes**, uses
(di-Me, [(methylsilylidene)tris(oxy)]tris-,
hydroxy-terminated, ethers with polyethylene-
polypropylene glycol monoalkyl ether, Silwet
L-722; antifoamant for silver halide photog. emulsions)

IT **Polysiloxanes**, uses
(di-Me, modified; antifoamants for silver halide photog. emulsions)

IT **Polyoxyalkylenes**, uses
(tall-oil fatty acid ester derivs.; antifoamant for silver halide photog. emulsions)

L37 ANSWER 24 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1997:421082 HCAPLUS
 DOCUMENT NUMBER: 127:57972
 TITLE: Electrophotographic image formation
 INVENTOR(S): Kato, Eiichi
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 42 pp.
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	-----	-----	-----	-----
	-----	-----	-----	-----
	JP 09106202	A2	19970422	JP 1996-208632

1996

0807 US 5725981 A 19980310 US 1996-692238

1996

0807 PRIORITY APPLN. INFO.: JP 1995-222778 A

1995

0809

AB The title image formation uses a photoreceptor having 2 laminated
 and
 peelable transfer layers to form an electrophotog. toner image
 then to thermally transfer the toner image to a recording
 material, wherein the 1st transfer layer is formed by
 electro-depositing thermoplastic resin particles containing 2
 kinds of
 specified resins with different softening point and glass
 transition point in 1 particle, and the 2nd transfer layer
 contains a different resin.

IT 190894-75-8 190894-78-1

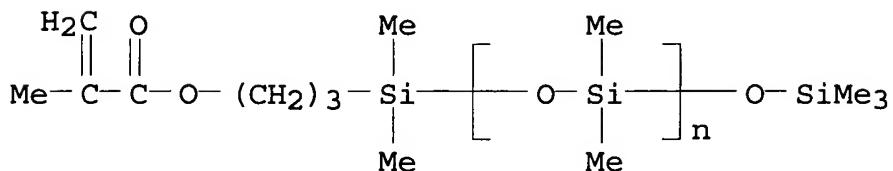
(used for increasing peeling ability of transfer layer for
 electrophotog. photoreceptor for image formation)

RN 190894-75-8 HCPLUS

CN 2-Propenoic acid, 2-methyl-, ethyl ester, polymer with
 α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]-
 ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)] and
 oxiranylmethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

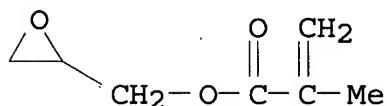
CM 1

CRN 123109-42-2
 CMF (C₂ H₆ O Si)_n C₁₂ H₂₆ O₃ Si₂
 CCI PMS



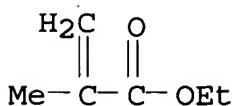
CM 2

CRN 106-91-2
 CMF C₇ H₁₀ O₃



CM 3

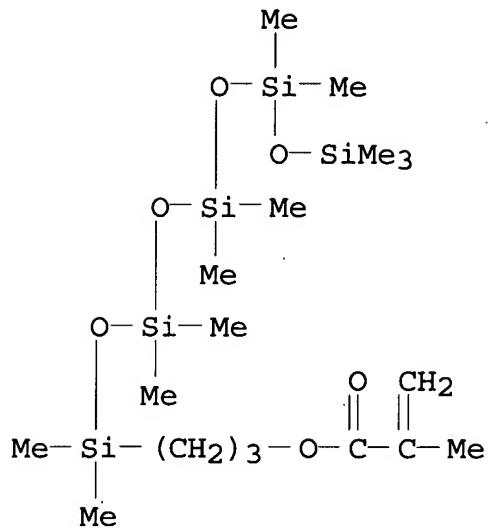
CRN 97-63-2
 CMF C₆ H₁₀ O₂



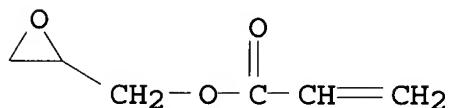
RN 190894-78-1 HCPLUS
 CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with methyl 2-propenoate, oxiranylmethyl 2-propenoate and 3-(undecamethylpentasiloxanyl)propyl 2-methyl-2-propenoate (9CI)
 (CA INDEX NAME)

CM 1

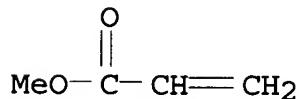
CRN 107642-12-6
 CMF C₁₈ H₄₄ O₆ Si₅



CM 2

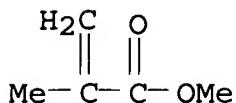
CRN 106-90-1
CMF C6 H8 O3

CM 3

CRN 96-33-3
CMF C4 H6 O2

CM 4

CRN 80-62-6
CMF C5 H8 O2



IC ICM G03G015-16
ICS G03G007-00; G03G015-01
CC 74-3 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT 58258-12-1 162127-42-6 166594-75-8 **190894-75-8**
190894-76-9 190894-77-0D, reaction products with thioethyl
methacrylate **190894-78-1** 190894-79-2 190894-81-6
(used for increasing peeling ability of transfer layer for
electrophotog. photoreceptor for image formation)

L37 ANSWER 25 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1997:119283 HCPLUS
DOCUMENT NUMBER: 126:132219
TITLE: Fluorine-containing epoxy resin composition
highly soluble in solvents for adhesives and
photocurable soil-repellent hard coatings

with

good adhesion for **ink-jet**
heads

INVENTOR(S): Imamura, Isao
PATENT ASSIGNEE(S): Canon K. K., Japan
SOURCE: PCT Int. Appl., 57 pp.
CODEN: PIXXD2
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	-----	-----	-----
-----	WO 9641835	A1	19961227	WO 1996-JP1606

1996

0613

W: US
RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC,
NL, PT, SE
EP 779337 A1 19970618 EP 1996-917664

1996

0613

EP 779337 B1 20011024
R: DE, FR, GB, IT
JP 10053639 A2 19980224 JP 1996-152366

1996

0613

JP 3478669 B2 20031215
US 2001008907 A1 20010719 US 1997-776747

1997

0404

US 6291545 B2 20010918 JP 1995-146269 A
PRIORITY APPLN. INFO.:

1995

0613

JP 1996-140192 A

1996

0603

WO 1996-JP1606 W

1996

0613

AB The title composition comprises 5-80% a polyfunctional epoxy resin

having ≥ 2 epoxy groups and being free from F or Si, 5-40% an epoxy compound having a perfluoro group at its terminal, and 5-80% a compound having ≥ 2 groups selected from epoxy, alc., carboxylate, amino and a mixture thereof together with F or Si.

An

adhesive for bonding alumite kettle lid and wood piece comprised
 Epikote 828 60, MF-120 10,
 1,3-bis(glycidoxypropyl)tetramethyldisiloxane 30, siloxane group-containing amine hardener LS7430 30,
 and

A-187 silane coupler 3 parts.

IT 186294-09-7P 186294-17-7P 186294-22-4P
 186294-28-0P 186294-30-4P

(fluorine-containing epoxy resin composition highly soluble
 in solvents for

adhesives and photocurable soil-repellent hard coatings with
 good adhesion for **ink-jet heads**)

RN 186294-09-7 HCAPLUS

CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with
 (chloromethyl)oxirane, 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane and

[(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluoroctyl)oxy]methyl]oxirane
 (9CI) (CA INDEX NAME)

CM 1

CRN 122193-68-4

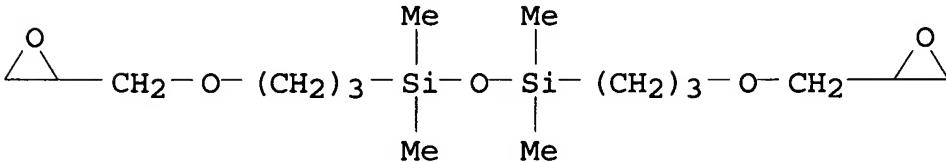
CMF C11 H9 F13 O2



CM 2

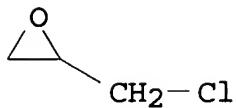
CRN 126-80-7

CMF C16 H34 O5 Si2



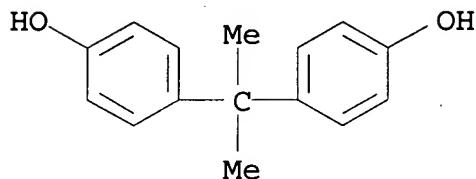
CM 3

CRN 106-89-8
 CMF C3 H5 Cl O



CM 4

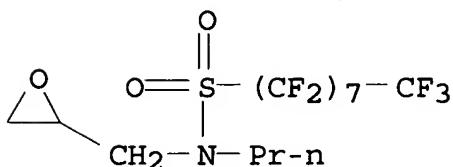
CRN 80-05-7
 CMF C15 H16 O2



RN 186294-17-7 HCPLUS
 CN 1-Octanesulfonamide, 1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-N-(oxiranylmethyl)-N-propyl-, polymer with 3-oxiranyl-7-oxabicyclo[4.1.0]heptane, $\alpha,\alpha,\alpha',\alpha'$ -tetrakis(trifluoromethyl)-1,4-benzenedimethanol and 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane (9CI) (CA INDEX NAME)

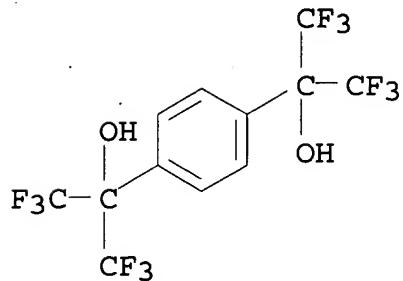
CM 1

CRN 77620-64-5
 CMF C14 H12 F17 N O3 S



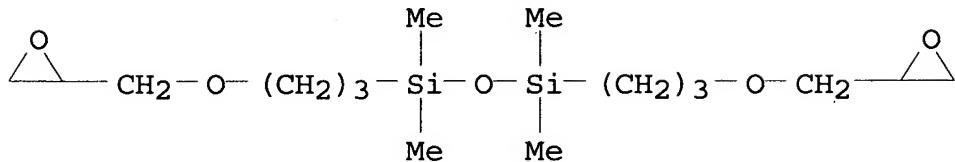
CM 2

CRN 1992-15-0
 CMF C12 H6 F12 O2



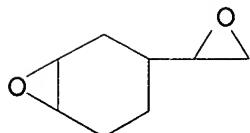
CM 3

CRN 126-80-7
 CMF C16 H34 O5 Si2



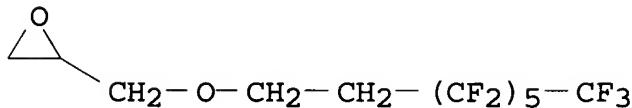
CM 4

CRN 106-87-6
 CMF C8 H12 O2

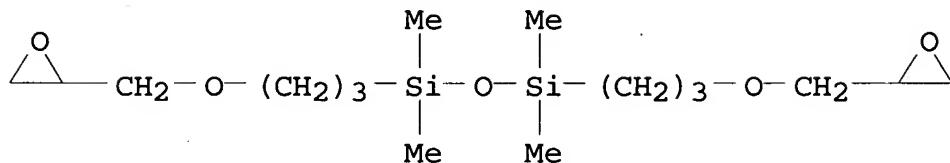


RN 186294-22-4 HCPLUS
 CN Disiloxane,
 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]-
 , polymer with [(3,3,4,4,5,5,6,6,7,7,8,8,8-
 tridecafluoroctyl)oxy]methyl]oxirane (9CI) (CA INDEX NAME)

CM 1

CRN 122193-68-4
CMF C11 H9 F13 O2

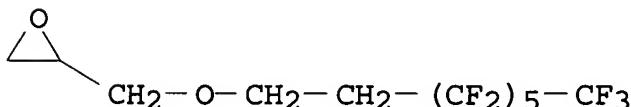
CM 2

CRN 126-80-7
CMF C16 H34 O5 Si2

RN 186294-28-0 HCPLUS

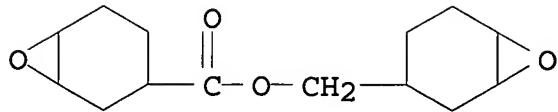
CN 7-Oxabicyclo[4.1.0]heptane-3-carboxylic acid, 7-oxabicyclo[4.1.0]hept-3-ylmethyl ester, polymer with 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]disiloxane and
[[[(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluoroctyl)oxy]methyl]oxiran (9CI) (CA INDEX NAME)

CM 1

CRN 122193-68-4
CMF C11 H9 F13 O2

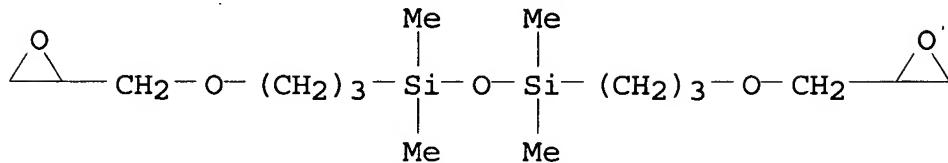
CM 2

CRN 2386-87-0
 CMF C14 H20 O4



CM 3

CRN 126-80-7
 CMF C16 H34 O5 Si2



RN 186294-30-4 HCPLUS
 CN Phenol, 4,4'-(1-methylethylidene)bis-, polymer with Cefral Coat A 101B, (chloromethyl)oxirane and 1,1,3,3-tetramethyl-1,3-bis[3-(oxiranemethoxy)propyl]disiloxane (9CI) (CA INDEX NAME)

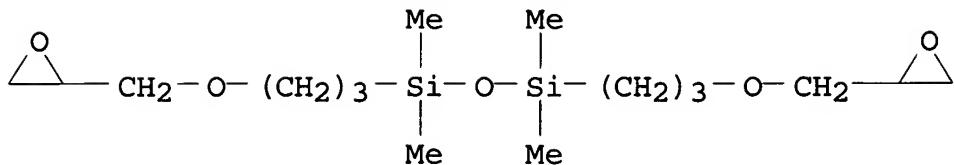
CM 1

CRN 137802-09-6
 CMF Unspecified
 CCI PMS, MAN

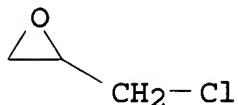
*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CM 2

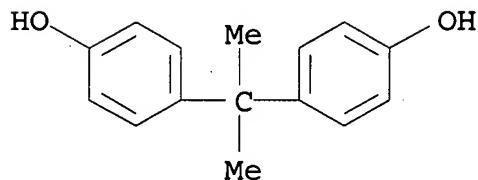
CRN 126-80-7
 CMF C16 H34 O5 Si2



CM 3

CRN 106-89-8
CMF C3 H5 Cl O

CM 4

CRN 80-05-7
CMF C15 H16 O2

IC ICM C08L063-00
 ICS C08G059-20; C08G059-40; C09D163-00; C09J163-00; B41J002-05
 CC 37-6 (Plastics Manufacture and Processing)
 Section cross-reference(s): 74
 ST epoxy compn fluorine contg adhesive; **ink jet**
 head epoxy resin; coating fluorine contg epoxy resin
 IT Adhesives
 Printing apparatus
 Ships
 (fluorine-containing epoxy resin composition highly soluble
 in solvents for
 adhesives and photocurable soil-repellent hard coatings with
 good adhesion for **ink-jet heads**)

IT Epoxy resins, uses

(fluorine-containing epoxy resin composition highly soluble in solvents for

adhesives and photocurable soil-repellent hard coatings with good adhesion for **ink-jet heads**)

IT Coating materials

(for ships; fluorine-containing epoxy resin composition highly soluble in

solvents for adhesives and photocurable soil-repellent hard coatings with good adhesion for **ink-jet heads**)

IT 30603-97-5P **186294-09-7P** 186294-11-1P 186294-13-3P

186294-15-5P **186294-17-7P** 186294-20-2P

186294-22-4P 186294-24-6P 186294-26-8P 186294-27-9P

186294-28-0P 186294-29-1P **186294-30-4P**

186294-32-6P

(fluorine-containing epoxy resin composition highly soluble in solvents for

adhesives and photocurable soil-repellent hard coatings with good adhesion for **ink-jet heads**)

L37 ANSWER 26 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1997:8913 HCAPLUS

DOCUMENT NUMBER: 126:39656

TITLE: Electrostatographic toner particles comprising

polysiloxane-modified resins

INVENTOR(S): Tavernier, Serge; Marien, August; Op De Beeck,

Werner

PATENT ASSIGNEE(S): Agfa-Gevaert Naamloze Vennootschap, Belg.

SOURCE: Eur. Pat. Appl., 23 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----
-----	-----	-----	-----
EP 740217	A1	19961030	EP 1996-200738

1996

0318

R: BE, DE, FR, GB, NL
US 5620825 A 19970415 US 1996-617327

1996

0318

JP 08297380 A2 19961112 JP 1996-90453

1996

0319

JP 3089206 B2 20000918
US 5888657 A 19990330 US 1997-786022

1997

0121

PRIORITY APPLN. INFO.: EP 1995-200723 A

1995

0323

US 1996-617327 A3

1996

0318

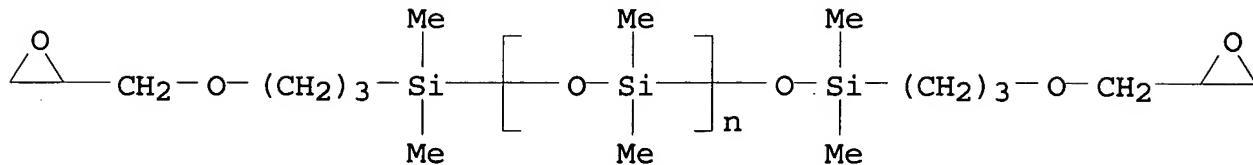
AB There are provided dry electrostatog. toner particles wherein the toner resin comprises more than 10% by weight of one or more polysiloxane-modified resins. In these resins the polysiloxane moieties are attached to the other polymeric moieties of the copolymers over an ether group or an ester group. In a preferred embodiment the toner resin of the toner particles consists of one or more polysiloxane-modified resins.

IT 130167-23-6

(reaction with linear polyesters for preparing electrostatog. toners)

RN 130167-23-6 HCPLUS

CN Poly[oxy(dimethylsilylene)], α -[dimethyl[3-(oxiranylmethoxy)propyl]silyl]- ω -[[dimethyl[3-(oxiranylmethoxy)propyl]silyl]oxy]- (9CI) (CA INDEX NAME)



IC ICM G03G009-087
 CC 74-3 (Radiation Chemistry, **Photochemistry**, and
 Photographic and Other Reprographic Processes)
 IT Recording
 (magneto-; toners containing polysiloxane-modified resins for)
 IT 130167-23-6
 (reaction with linear polyesters for preparing electrostatog..
 toners)

L37 ANSWER 27 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1996:595883 HCPLUS

DOCUMENT NUMBER: 125:234486

TITLE: Photosensitive composition for volume
 hologram

recording, recording medium
 using the same and volume hologram formation
 method

INVENTOR(S): Sato, Masahiko; Mizutani, Kenzo; Kawabata,
 Masami; Sumyoshi, Iwao

PATENT ASSIGNEE(S): Nippon Paint Co Ltd, Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----
-----	-----	-----	-----
JP 08160842	A2	19960621	JP 1995-254947

1995

1002

JP 3532675	B2	20040531	
US 5702846	A	19971230	US 1997-808546

1997

0228

PRIORITY APPLN. INFO.:

JP 1994-238927

A1

1994

1003

US 1995-536103

B1

1995

0929

AB In the title composition comprising a cationic polymerizable compound, a

radical polymerizable compound, a cationic polymerization initiator and a

radical polymerization initiator, the cationic polymerizable compound

and/or the radical polymerizable compound contain siloxane linkage.

The radical polymerization initiator may contain a cyanine dye as a

sensitizer and a diaryl iodonium salt as an active radical generation compound The composition showed excellent light-resistance

and heat-resistance.

IT 31305-85-8, TSL 9906

(siloxane linkage-containing cationic polymerizable compound of

photosensitive composition for volume hologram **recording**)

RN 31305-85-8 HCPLUS

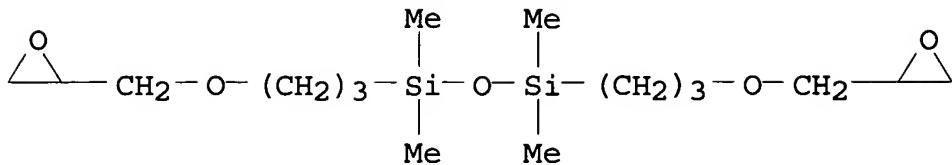
CN Disiloxane,

1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 126-80-7

CMF C16 H34 O5 Si2



IC ICM G03H001-02
 ICS C08G059-40; G02B001-04; G03F007-004; G03F007-027;
 G03F007-029; G03F007-075; G03H001-04; G03H001-28
 CC 74-8 (Radiation Chemistry, **Photochemistry**, and
 Photographic and Other Reprographic Processes)
 ST photosensitive compn vol hologram **recording**
 IT Holography
 (photosensitive composition for volume hologram **recording**,
 recording medium using the same and volume hologram
 formation method)
 IT Recording materials
 (holog., photosensitive composition for volume hologram
 recording, recording medium using the same
 and volume hologram formation method)
 IT Holography
 (recording materials, photosensitive composition for volume
 hologram **recording**, recording medium using
 the same and volume hologram formation method)
 IT 17578-95-9 66003-76-7, Diphenyliodonium
 trifluoromethanesulfonate
 (radical polymerization initiator of photosensitive
 composition for volume
 hologram **recording**)
 IT 31305-85-8, TSL 9906 121225-97-6, XC 96B0370
 (siloxane linkage-containing cationic polymerizable compound
 of
 photosensitive composition for volume hologram **recording**)
 IT 18151-85-4, TSL 9705 18547-93-8, TSL 9706 178953-28-1, PS 2A
 (siloxane linkage-containing radical polymerizable compound of
 photosensitive composition for volume hologram **recording**)

L37 ANSWER 28 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1996:449206 HCPLUS

DOCUMENT NUMBER: 125:100301

TITLE: Photosensitive composition, volume hologram
recording material using it, hologram,
 and its formation

INVENTOR(S): Sato, Masahiko; Mizutani, Kenzo; Kawabata,
 Masami; Sumiyoshi, Iwao

PATENT ASSIGNEE(S) : Nippon Paint Co Ltd, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			
-----	-----	-----	-----
-----	-----	-----	-----
JP 08101500	A2	19960416	JP 1994-238932

1994

1003
 JP 3532621 B2 20040531

PRIORITY APPLN. INFO.: JP 1994-238932

1994

1003

AB The composition contains (A) a siloxane-containing polymer binder (B) a radically polymerizable compound, (C) a cationic polymerizable compound, (D) a radical polymerization initiator, and (E) a cationic polymerization initiator. The material has a **recording** layer obtained from the composition. The title **recording** method involves the steps of (A) exposing the material to a laser or coherence interference pattern and (B) irradiating with UV light and/or visible light and/or (C) heating. The obtained hologram with good heat and light resistance is also claimed.

IT 31305-85-8P

(siloxane-containing photosensitive composition for volume hologram

recording material and formation of hologram)

RN 31305-85-8 HCPLUS

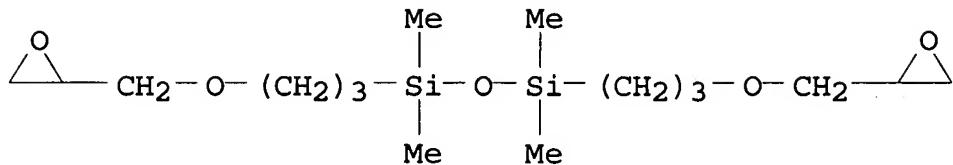
CN Disiloxane,

1,1,3,3-tetramethyl-1,3-bis[3-(oxiranylmethoxy)propyl]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 126-80-7

CMF C16 H34 O5 Si2



IC ICM G03F007-004
 ICS G03F007-027; G03F007-029; G03F007-033; G03F007-075;
 G03F007-20; G03H001-02; G03H001-04

CC 74-8 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38

IT Dyes, cyanine
 (sensitizer; siloxane-containing photosensitive composition
 for volume
 hologram **recording** material and formation of
 hologram)

IT Holography
 Photoimaging compositions and processes
 Polymerization catalysts
 (siloxane-containing photosensitive composition for volume
 hologram
recording material and formation of hologram)

IT Siloxanes and Silicones, uses
 (siloxane-containing photosensitive composition for volume
 hologram
recording material and formation of hologram)

IT 66003-76-7, Diphenyliodonium trifluoromethanesulfonate
 104558-94-3, UVI 6974 146297-31-6
 (siloxane-containing photosensitive composition for volume
 hologram
recording material and formation of hologram)

IT 9051-49-4P, Pentaerythritol-propylene oxide copolymer
 31305-85-8P 143410-64-4P 178953-29-2P 178953-32-7P
 (siloxane-containing photosensitive composition for volume
 hologram
recording material and formation of hologram)

IT 178953-30-5, Ethyl acrylate-TSL 9705 copolymer
 (siloxane-containing photosensitive composition for volume
 hologram
recording material and formation of hologram)

ACCESSION NUMBER: 1996:280445 HCPLUS
 DOCUMENT NUMBER: 124:292552
 TITLE: Aqueous surface treating agents for plastic
 films for magnetic tapes or thermal-transfer
 sheets
 INVENTOR(S): Iguchi, Yoshinori; Takahashi, Naohiro;
 Kuwata, Satoshi
 PATENT ASSIGNEE(S): Shinetsu Chemical Industry. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	JP 08045070	A2	19960216	JP 1994-182043

1994

0803	JP 3481683	B2	20031222	JP 1994-182043
PRIORITY APPLN. INFO.:				

1994

0803

AB Title agents, with good adhesion, comprise (A) aqueous dispersions of branched non-fluidable silicones containing $R_1SiO_2/2$ and $R_1SiO_3/2$ (R1 = C1-20 hydrocarbyl), (B) aqueous dispersions of $R_2R_3N(CH_2)_a[NR_4(CH_2)_b]cSiR_5(OR_6)_2$ ($R_2-R_4 = H$, C1-6 hydrocarbyl; R5, R6 = C1-6 hydrocarbyl; a, b = 1-6; c = 0-3) hydrolyzates, and (C) aqueous polyurethanes at an effective component of A/B/C of 9-90:0.1-40:9-90. An aqueous composition containing

49.4:0.6:50.0

octamethylcyclotetrasiloxane-phenyltriethoxysilane copolymer/3-aminopropylmethyldimethoxysilane/Elastron H 3 (reactive polyester-polyurethane) was applied on a PET film and baked to form a film showing dynamic friction coefficient 0.17 and good

soil resistance.

IT 170099-69-1

(aminosiloxane/polyurethane-containing aq coatings for plastic films for magnetic tapes or thermal-transfer sheets)

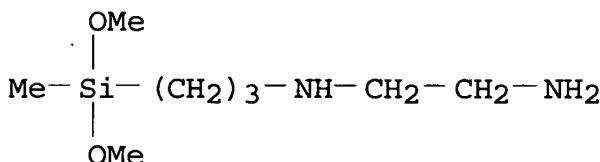
RN 170099-69-1 HCAPLUS

CN 1,2-Ethanediamine, N-[3-(dimethoxymethylsilyl)propyl]-, polymer with diethoxymethyl[3-(oxiranylmethoxy)propyl]silane, octamethylcyclotetrasiloxane and triethoxyphenylsilane (9CI) (CA INDEX NAME)

CM 1

CRN 3069-29-2

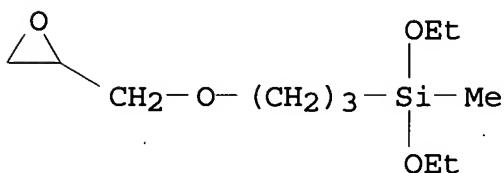
CMF C8 H22 N2 O2 Si



CM 2

CRN 2897-60-1

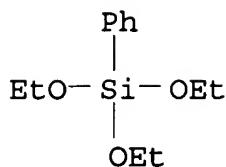
CMF C11 H24 O4 Si



CM 3

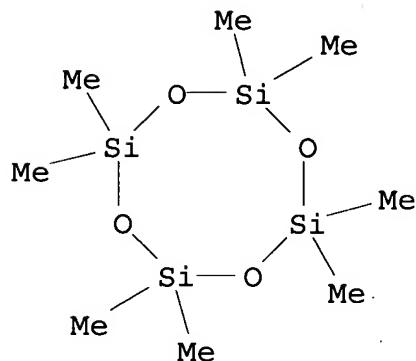
CRN 780-69-8

CMF C12 H20 O3 Si



CM 4

CRN 556-67-2
 CMF C8 H24 O4 Si4



IC ICM G11B005-84
 ICS B41M005-40; C08K005-54; C08L075-04; C08L083-04; C09D175-04;
 C09D183-04
 ICA B42D015-10
 CC 42-10 (Coatings, Inks, and Related Products)
 Section cross-reference(s): 74, 77
 IT **Recording apparatus**
 (aminosiloxane/polyurethane-containing aq
 coatings
 for plastic films for magnetic tapes or thermal-transfer
 sheets)
 IT 118478-14-1, **Superflex 110 170099-69-1**
 (aminosiloxane/polyurethane-containing aq coatings for plastic
 films for magnetic tapes or thermal-transfer sheets)

L37 ANSWER 30 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:849672 HCAPLUS

DOCUMENT NUMBER: 124:11046

TITLE: Water-based crosslinked siloxane-vinyl

INVENTOR(S) : compound copolymer emulsions for coatings
 Noda, Itsupei; Ishikawa, Masami; Yamawaki, Masaji
 PATENT ASSIGNEE(S) : Takemoto Oil & Fat Co Ltd, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	-----	-----	-----
-----	JP 07196750	A2	19950801	JP 1993-355410
1993				
1229	JP 3361593	B2	20030107	JP 1993-355410

PRIORITY APPLN. INFO.:

1993

1229

AB The compns. comprise 90-99/1-10 mixts. of linear units comprising R1R2SiO, R3SiX1O (I), and/or R4Si(Z1Y1)O (II) and crosslinked units comprising R5SiO3/2, SiX2O3/2 (III), Si(Z2Y2)O3/2 (IV), and/or SiO2 [R1-R5 = radically nonpolymerizable hydrocarbyl; X1, X2 = radically nonpolymerizable epoxy-containing group-substituted

hydrocarbyl; Y1, Y2 = glycidyl (meth)acrylate-C1-4-alkyl (meth)acrylate (in 1-99:1-99 weight ratio) graft copolymerd. segment;

Z1, Z2 = divalent organic linking group], in which I + III form 0.5-15 mol%, II + IV form 0.5-5 mol%, and Y1 + Y2 form 25-75 weight%.

The compns. are useful for magnetic **recording** materials, printing plates, photog. materials, etc., showing surface smoothness and affinity to **inks** or adhesives. Thus, 97.7 g octamethylcyclotetrasiloxane was polymerized with 4.7 g (γ -glycidoxypropyl)trimethoxysilane and 5.0 g (γ -methacryloyloxypropyl)trimethoxysilane, then further treated with 100 g 48:48:4 mixture of Et acrylate, Me methacrylate,

and glycidyl methacrylate and K persulfate to give an aqueous emulsion, which was applied to a film to give a test piece showing

good peeling resistance.

IT 171609-55-5P

(aqueous emulsions of siloxane-acrylate graft copolymers for coatings)

RN 171609-55-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with dimethoxymethyl[2-(oxiranylmethoxy)ethyl]silane, ethyl

2-propenoate, octamethylcyclotetrasiloxane, oxiranylmethyl 2-methyl-2-propenoate, trimethoxymethylsilane and

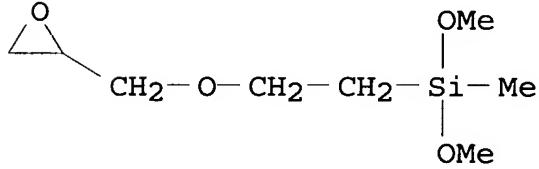
3-(trimethoxysilyl)propyl 2-methyl-2-propenoate, graft (9CI) (CA INDEX NAME)

INDEX NAME

CM 1

CRN 171609-54-4
SME 62 W18 84 S

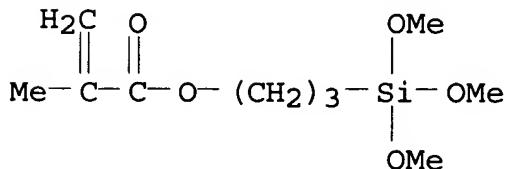
CMF C8 H18 O4 Si



CM 2

CRN 2530-85-0

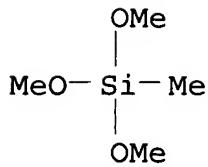
CMF C10 H20 O5 Si



CM 3

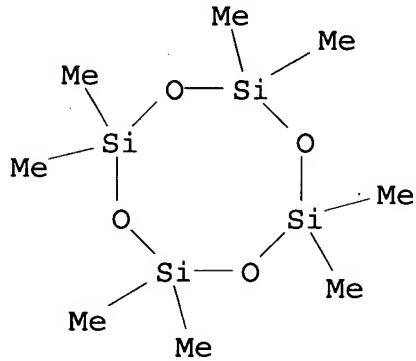
CRN 1185-55-3

CMF C4 H12 O3 Si



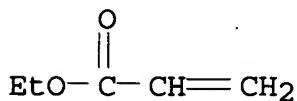
CM 4

CRN 556-67-2
 CMF C8 H24 O4 Si4



CM 5

CRN 140-88-5
 CMF C5 H8 O2



CM 6

CRN 106-91-2
 CMF C7 H10 O3

0629

JP 3552060
US 5534322B2 20040811
A 19960709

US 1994-231749

1994

0425

PRIORITY APPLN. INFO.:

JP 1993-158388

A

1993

0629

JP 1994-55725

A

1994

0325

AB The title materials comprise (A) polymerizable compds. containing (meth)acryloyl groups, (B) reactive-functional group-containing antistatic agents containing quaternary ammonium salt groups, ethylene glycol chains, C \geq 4 hydrocarbon groups, and polymerizable groups, and (C) silicone compds.

IT 165182-57-0P

(antistatic coating materials for recording media)

RN 165182-57-0 HCPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(dihydroxymethylsilyl)propyl ester,

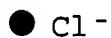
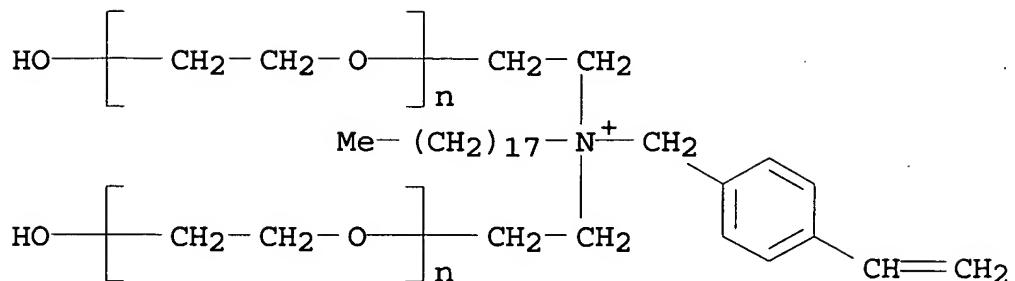
polymer with dimethylsilanediol, α,α' -[[[(4-ethenylphenyl)methyl]octadecyliminio]di-2,1-ethanediyl]bis[ω -hydroxypoly(oxy-1,2-ethanediyl)] dichloride, α -hydro- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl) ether with 2-ethyl-2-(hydroxymethyl)-1,3-propanediol (3:1), methylsilanediol, oxirane and α -(1-oxo-2-propenyl)- ω -[(1-oxo-2-propenyl)oxy]poly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME)

CM 1

CRN 159969-22-9

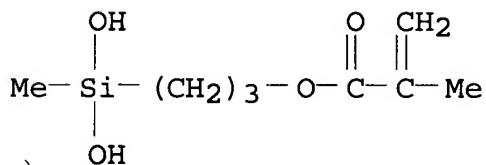
CMF (C₂ H₄ O)_n (C₂ H₄ O)_n C₃₁ H₅₆ N O₂ . Cl

CCI PMS



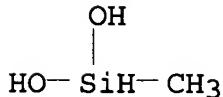
CM 2

CRN 156787-79-0
CMF C8 H16 O4 Si



CM 3

CRN 43641-90-3
CMF C H6 O2 Si

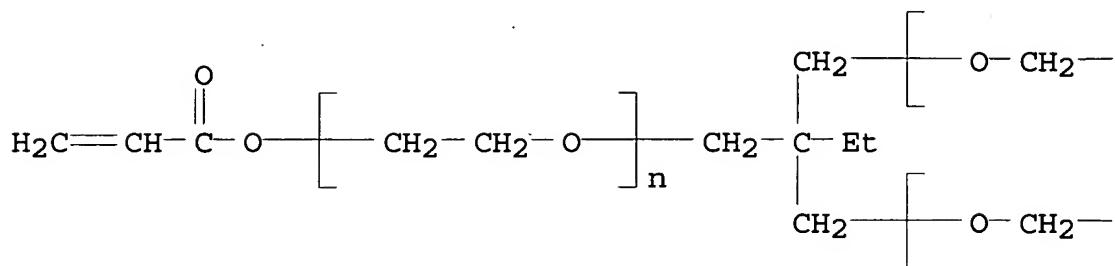


CM 4

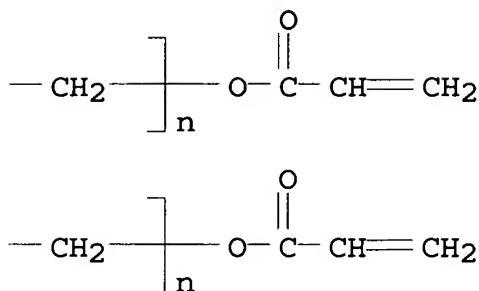
CRN 28961-43-5
CMF (C₂ H₄ O)n (C₂ H₄ O)n (C₂ H₄ O)n C₁₅ H₂₀ O₆

CCI PMS

PAGE 1-A

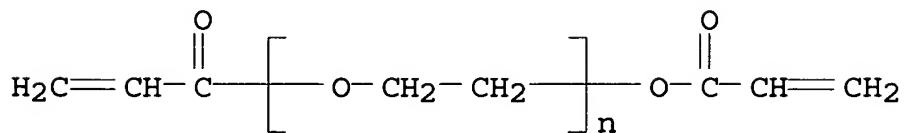


PAGE 1 - B



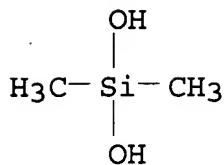
CM 5

CRN 26570-48-9
CMF (C2 H4 O)n C6 H6 O3
CCI PMS



CM 6

CRN 1066-42-8
CMF C2 H8 O2 Si



CM 7

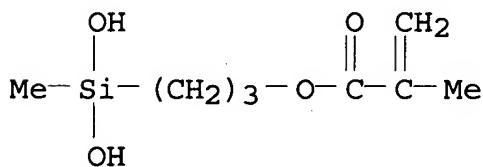
CRN 75-21-8
CMF C2 H4 O



IT 201419-38-7DP, trtrimethylsilyl-terminated
(polymerizable silicone compds. of antistatic coating
materials)
RN 201419-38-7 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, 3-(dihydroxymethylsilyl)propyl
ester,
polymer with dimethylsilanediol, methylsilanediol and oxirane,
graft (9CI) (CA INDEX NAME)

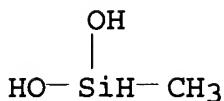
CM 1

CRN 156787-79-0
CMF C8 H16 04 Si

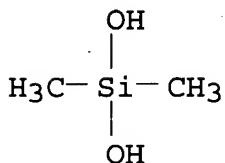


CM 2

CRN 43641-90-3
CMF C H6 O2 Si



CM 3

CRN 1066-42-8
CMF C2 H8 O2 Si

CM 4

CRN 75-21-8
CMF C2 H4 O

IC ICM C09K003-16
ICS C09K003-16; G11B007-24
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 42, 77
ST antistatic coating material **recording** media
IT Coating materials
(antistatic, antistatic coating materials for **recording** media)
IT Memory devices
(magnetooptical disks, antistatic coating materials for **recording** media)
IT Memory devices
(optical disks, read-only, antistatic coating materials for **recording** media)

IT Coating materials
 (photocurable, scratch-resistant, antistatic coating materials
 for **recording** media)

IT 165182-56-9P 165182-57-0P 165182-58-1P
 (antistatic coating materials for **recording** media)

IT 201419-38-7DP, trrimethylsilyl-terminated
 (polymerizable silicone compds. of antistatic coating
 materials)

L37 ANSWER 32 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:621508 HCPLUS
 DOCUMENT NUMBER: 123:22083
 TITLE: Method and apparatus for forming
 electrophotographic color transferred image
 INVENTOR(S): Kato, Eiichi; Osawa, Sadao; Nakazawa, Yusuke
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: PCT Int. Appl., 108 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
	-----	-----	-----	-----
	-----	-----	-----	-----
	WO 9423345	A1	19941013	WO 1994-JP487

1994

0325

W: JP, US
 RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL,
 PT, SE
 JP 06337599 A2 19941206 JP 1993-349754

1993

1228

EP 651295 A1 19950503 EP 1994-910540

1994

0325

EP 651295 B1 19980610
 R: DE, GB

US 5747214

A

19980505

US 1994-343476

1994

1125

PRIORITY APPLN. INFO.:

JP 1993-90488

A

1993

0326

JP 1993-93832

A

1993

0330

WO 1994-JP487

W

1994

0325

AB On the surface of an electrophotog. photosensitive element, a compound containing fluorine atoms and/or silicon atoms is provided in

order to form a peelable transfer layer on the photosensitive element, a toner image of ≥ 1 colors is formed on the transfer layer by electrophotog. process, and then the toner image

is transferred to a transfer material together with the transfer layer. A color copy of high-definition and high quality can be easily and stably obtained without any color misregistration, and a color image with stable preservability can be formed.

IC ICM G03G013-16

ICS G03G015-16

CC 74-3 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)

IT Rubber, silicone, uses

Siloxanes and Silicones, uses
(transfer layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(aminoalkyl di-Me, KF 804; transfer layer
for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(carboxy-containing, X-22-3701E; transfer layer for
electrophotog.

photoreceptor)

IT **Siloxanes** and Silicones, uses
(di-Me, transfer layer for electrophotog.
photoreceptor)

IT **Polyoxyalkylenes**, uses
(di-Me siloxane-, transfer layer
for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(di-Me, 3-hydroxypropyl Me, ethoxylated,
transfer layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(di-Me, [(methylsilylidyne)tris(oxy)]tris-,
hydroxy-terminated, ethers with **polyethylene-**
polypropylene glycol monoalkyl ether,
transfer layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(di-Me, carboxy-terminated, TSF 4770; TSF
411; transfer layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(di-Me, epoxy-containing, XF42-A5041; transfer
layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(di-Me, mercaptopropyl group-terminated,
transfer layer for electrophotog. photoreceptor)

IT **Siloxanes** and Silicones, uses
(di-Me, **Polyoxyalkylene**-,
transfer layer for electrophotog. photoreceptor)

IT **Polyoxyalkylenes**, uses
(fluorine-containing, transfer layer for electrophotog.
photoreceptor)

IT **Siloxanes** and Silicones, uses
(hydroxy-terminated, transfer layer for electrophotog.
photoreceptor)

IT Fluoropolymers
Siloxanes and Silicones, uses
(**Polyoxyalkylene**-, transfer layer for electrophotog.
photoreceptor)

IT **Polyoxyalkylenes**, uses
(siloxane-, transfer layer for electrophotog.
photoreceptor)

IT 75-21-8D, Oxirane, reaction products with **siloxanes**
82030-84-0, SURFLONS141 91105-71-4, SURFLONS-382 144070-79-1
163916-20-9 163916-21-0 163916-22-1 163916-23-2
163916-24-3 163916-27-6 163916-28-7 163916-29-8
164104-57-8 173611-09-1
(transfer layer for electrophotog. photoreceptor)

L37 ANSWER 33 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1995:248292 HCPLUS
 DOCUMENT NUMBER: 122:20401
 TITLE: Magnetic particles used for
 electrophotographic and electrostatic
 recording, and manufacture thereof
 INVENTOR(S): Shiozaki, Masaya; Kikuta, Shinji; Edahiro,
 Kazuhisa
 PATENT ASSIGNEE(S): Mita Industrial Co Ltd, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----	-----
	-----	-----	-----	-----
	JP 06102708	A2	19940415	JP 1992-253138

1992

0922

JP 3216916	B2	20011009	JP 1992-253138
PRIORITY APPLN. INFO.:			

1992

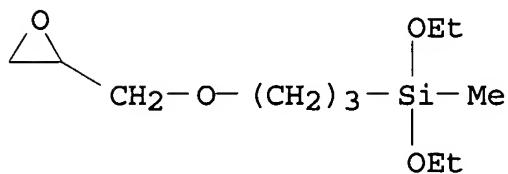
0922

AB The title magnetic particles comprise magnetic powder whose
 surface is bonded with a polymer via a coupling agent. The
 manufacture
 comprises processing the powder with the coupling agent to
 introduce a functional group on the surface, attaching a
 polymerization
 initiator to the functional group, and polymerizing a vinyl
 monomer in
 a dispersed medium containing the particles. The magnetic
 particles
 exhibited excellent dispersibility and affinity with a binder
 resin.
 IT 159654-95-2P
 (magnetic particles bonded with polymers)
 RN 159654-95-2 HCPLUS

CN · 2-Propenoic acid, 2-methyl-, butyl ester, polymer with
 diethenylbenzene,
 diethoxymethyl [3-(oxiranylmethoxy)propyl]silane,
 ethenylbenzene and 2,2'-oxybis[ethanol] (9CI) (CA INDEX NAME)

CM 1

CRN 2897-60-1
 CMF C11 H24 O4 Si



CM 2

CRN 1321-74-0
 CMF C10 H10
 CCI IDS



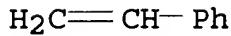
2 [D1-CH=CH2]

CM 3

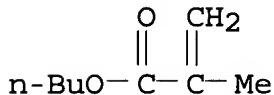
CRN 111-46-6
 CMF C4 H10 O3

HO-CH2-CH2-O-CH2-CH2-OH

CM 4

CRN 100-42-5
CMF C8 H8

CM 5

CRN 97-88-1
CMF C8 H14 O2

IC ICM G03G009-107
 ICS C08F002-00; C08F002-18; C08F002-44; C08F004-02; G03G009-083
 CC 74-3 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 Section cross-reference(s): 38
 ST magnetic particle electrophotog; electrostatic **recording**
 magnetic particle
 IT **Recording**
 (elec., magnetic particles bonded with polymers)
 IT 159654-94-1P **159654-95-2P** 159654-96-3P
 (magnetic particles bonded with polymers)

L37 ANSWER 34 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1995:192032 HCPLUS
 DOCUMENT NUMBER: 122:20587
 TITLE: Thermal transfer dye-donating material
 INVENTOR(S): Kubodera, Seiichi
 PATENT ASSIGNEE(S): Fuji Photo Film Co Ltd, Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 31 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.
DATE			

JP 06099667 A2 19940412 JP 1992-276834

1992

0922

PRIORITY APPLN. INFO.:

JP 1992-276834

1992

0922

AB The title material is obtained by coating and drying on a support a dye-donating layer composition containing a thermal migration type dye, a binder resin, a mold releasing agent, and a F-containing compound in an organic solvent of b.p. 100-170°. The thermal transfer dye-donating material can give stable images with high-d. and sharpness.

IC ICM B41M005-30

CC 74-7 (Radiation Chemistry, **Photochemistry**, and **Photographic** and Other Reprographic Processes)
Section cross-reference(s): 42

IT **Siloxanes** and Silicones, uses

(amino, as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Polyoxyalkylenes**, uses

(di-Me siloxane-, as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Siloxanes** and Silicones, uses

(di-Me, hydroxypropyl Me, ethers with polyethylene-polypropylene glycol mono-Pr ether, [(trimethylsilyl)oxy]-terminated; as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Siloxanes** and Silicones, uses

(di-Me, polyoxyalkylene-, as mold releasing agent contained in thermal transfer dye-donating type material)

IT **Siloxanes** and Silicones, uses

(epoxy, as mold releasing agent contained in thermal transfer

IT dye-donating type material)
Epoxy resins, uses
 (siloxane-, as mold releasing agent contained in
 thermal transfer dye-donating type material)

L37 ANSWER 35 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 1994:545411 HCAPLUS
DOCUMENT NUMBER: 121:145411
TITLE: Thermal transfer **recording** material
INVENTOR(S): Tanaka, Kazuyoshi; Hashimoto, Yutaka; Kamei,
 Masayuki
PATENT ASSIGNEE(S): Dainippon Ink & Chemicals, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 16 pp.
 CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.
DATE	-----	-----	-----	-----
	JP 05185757	A2	19930727	JP 1992-4835

1992

0114

JP 3209281 B2 20010917
PRIORITY APPLN. INFO.: JP 1992-4835

1992

0114

AB In the title material consisting of a base film, an **ink** layer on 1 side of the base film, and a synthetic resin layer on the other side, the above resin layer contains a resin containing fluorinated-alkyl and polyorganosiloxane groups and, optionally, in addition, polyoxyalkylene or polyoxyalkylene and alkyl groups.

The above resin consists of a polymer obtained from a fluorinated-alkyl group-containing ethylenic monomer and a polyorgnosiloxy group-containing ethylenic monomer and, optionally, in addition, a polyoxyalkylene group-containing ethylenic monomer and

alkylene group-containing ethylenic monomer. The material treated

with the above resin has anti-sticking characteristics and provides high-resolution and high-quality printings at high speed printing.

IT 157382-57-5

(treatment agent containing, thermal printing material treated)

RN 157382-57-5 HCPLUS

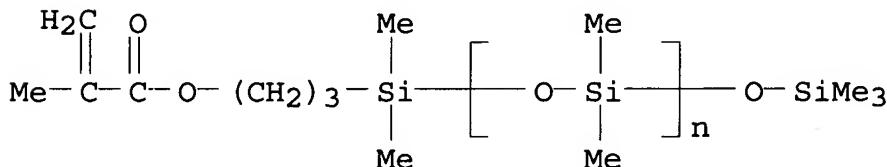
CN 2-Propenoic acid, dodecyl ester, polymer with α -[dimethyl[3-[(2-methyl-1-oxo-2-propenyl)oxy]propyl]silyl]- ω -[(trimethylsilyl)oxy]poly[oxy(dimethylsilylene)], α -(ethenyldimethylsilyl)- ω -[(ethenyldimethylsilyl)oxy]poly[oxy(dimethylsilylene)], 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and methyloxirane polymer with oxirane 2-[(1-oxo-2-propenyl)oxy]ethyl ester (9CI) (CA INDEX NAME)

CM 1

CRN 123109-42-2

CMF (C₂ H₆ O Si)_n C₁₂ H₂₆ O₃ Si₂

CCI PMS

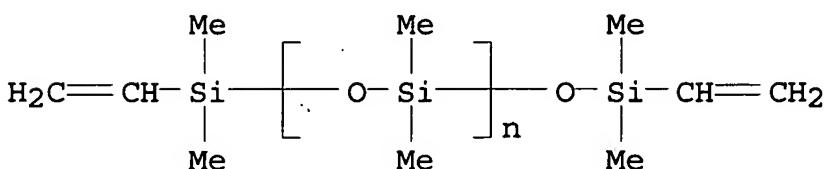


CM 2

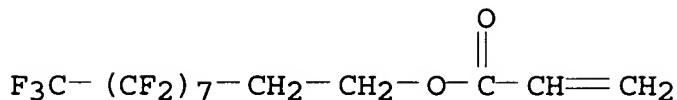
CRN 59942-04-0

CMF (C₂ H₆ O Si)_n C₈ H₁₈ O Si₂

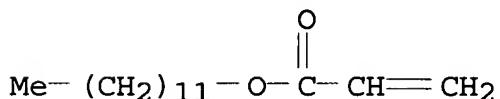
CCI PMS



CM 3

CRN 27905-45-9
CMF C13 H7 F17 O2

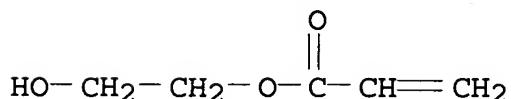
CM 4

CRN 2156-97-0
CMF C15 H28 O2

CM 5

CRN 157184-95-7
CMF C5 H8 O3 . x (C3 H6 O . C2 H4 O)x

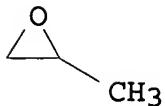
CM 6

CRN 818-61-1
CMF C5 H8 O3

CM 7

CRN 9003-11-6
CMF (C3 H6 O . C2 H4 O)x
CCI PMS

CM 8

CRN 75-56-9
CMF C3 H6 O

CM 9

CRN 75-21-8
CMF C2 H4 O

IC ICM B41M005-40
 CC 74-6 (Radiation Chemistry, **Photochemistry**, and
Photographic and Other Reprographic Processes)
 IT 156932-33-1 156932-35-3 156932-36-4 156932-38-6
 156932-40-0 156932-44-4 156932-45-5 156932-47-7
 156932-48-8 157177-62-3 **157382-57-5**
 (treatment agent containing, thermal printing material
 treated)

L37 ANSWER 36 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1994:422385 HCPLUS
 DOCUMENT NUMBER: 121:22385
 TITLE: Ternary surfactant system to reduce static
 charges in silver halide photographic
 material
 INVENTOR(S): Schoenberg, Allan R.; Shu, Ming Tsai
 PATENT ASSIGNEE(S): du Pont de Nemours, E. I., and Co., USA
 SOURCE: U.S., 8 pp. Cont. of U.S. Ser. No. 627,872,
 abandoned.
 CODEN: USXXAM
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.	
DATE	-----	-----	-----	-----	
	US 5258276	A	19931102	US 1992-885063	
1992					
0515					
PRIORITY APPLN. INFO.:				US 1987-129805	B1
1987					
1207					
				US 1990-511801	B1
1990					
0416					
				US 1990-627872	B1
1990					
1213					
AB	A ternary surfactant system useful in reducing the propensity of a silver halide photog. material to generate unwanted static charges				
	is described. This ternary system comprises a mixture of a specific				
	anionic and two specific nonionic surfactants and produces a surprising synergistic result. A solution of this ternary system is				
	also useful in reducing static charges produced on the surface of an x-ray intensifying screen.				
IC	ICM	G03C001-85			
NCL	430527000				
CC	74-2 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)				
IT	Siloxanes and Silicones, properties (ternary surfactant systems containing, for reducing static charges in silver halide photog. materials)				

IT **Siloxanes** and Silicones, uses
 (di-Me, 3-hydroxypropyl Me, ethers with
 polyethylene-polypropylene glycol
 mono-Me ether, with polyethylene-
 polypropylene glycol mono-Me ether, ternary
 surfactant systems containing Silwet L 77, for reducing static
 charges in silver halide photog. materials)

IT **Siloxanes** and Silicones, uses
 (di-Me, 3-hydroxypropyl Me, ethoxylated
 propoxylated, ternary surfactant systems containing ABIL B
 8843,
 for reducing static charges in silver halide photog.
 materials)

IT **Polyoxyalkylenes**, uses
 (di-Me, Me hydrogen **siloxane**-,
 ternary surfactant systems containing Dow Corning 193, for
 reducing
 static charges in silver halide photog. materials)

IT **Siloxanes** and Silicones, uses
 (di-Me, Me hydrogen,
polyoxyalkylene-, ternary surfactant systems containing Dow
 Corning 193, for reducing static charges in silver halide
 photog. materials)

IT **Siloxanes** and Silicones, uses
 (polyether-, ternary surfactant systems containing, for
 reducing
 static charges in silver halide photog. materials)

L37 ANSWER 37 OF 38 HCPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1990:506510 HCPLUS
 DOCUMENT NUMBER: 113:106510
 TITLE: Receptor sheet for sublimation-type thermal
 transfer **recording**
 INVENTOR(S): Ichii, Masaru; Fukuda, Kozo; Komine, Tsutomu
 PATENT ASSIGNEE(S): Nisshinbo Industries, Inc., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 6 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

DATE	PATENT NO.	KIND	DATE	APPLICATION NO.
-----	-----	-----	-----	-----
	JP 01232096	A2	19890918	JP 1988-58344

1988

0314

PRIORITY APPLN. INFO.:

JP 1988-58344

1988

0314

AB In obtaining the title receptor sheet by forming a dye-receiving layer with a water-based binder, the above layer is formed with a mixed solution containing a water-based saturated polyester resin, an

associate-type thickener, and a (mold) release agent. The associate-type thickener is a nonionic-type thickener and the release

agent is selected from amino-modified silicones and silane derivs.

and reaction products of amine-reactive compds.

IT 101638-90-8

(thermal-transfer printing receptor sheets containing)

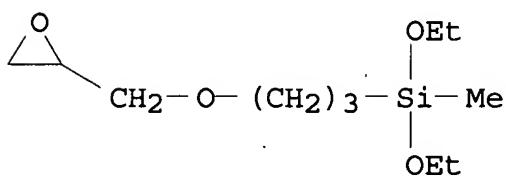
RN 101638-90-8 HCPLUS

CN Silane, diethoxymethyl[3-(oxiranylmethoxy)propyl]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 2897-60-1

CMF C11 H24 O4 Si



IC ICM B41M005-26

ICS D21H001-28; D21H005-00

CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST thermal transfer receptor sheet; recording thermal transfer receptor sheet; copying thermal transfer receptor sheet

IT 3069-29-2 101638-90-8 101962-84-9, Borchigel-L-75
128004-35-3, QR 1001

(thermal-transfer printing receptor sheets containing)

L37 ANSWER 38 OF 38 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1978:24332 HCAPLUS
 DOCUMENT NUMBER: 88:24332
 TITLE: Stabilization of chromium dioxide magnetic
 pigments
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AB CrO₂ pigments are stabilized against loss of magnetic properties by treatment in aqueous or alc. suspension with **polyoxyalkylene**-siloxane block polymers and drying at 50-200°. Thus, 40 parts CrO₂ in 110 parts H₂O is stirred with 4.8 parts **polyethylene-polypropylene glycol-dimethyl** siloxane ether 2 h at 40° and pH 3.6-3.9, filtered, and dried 8 h at 90°. Magnetic tape containing this CrO₂ has orientation factor 3.22 and time at 65° and 95% relative humidity for loss of 10% magnetic saturation 18.0 day, compared with 2.67 and 6.3, resp., for untreated CrO₂.

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CC 42-5 (Coatings, Inks, and Related Products)
Section cross-reference(s): 77ST chromium dioxide magnetic stabilization; pigment magnetic stabilization; siloxane stabilizer magnetic pigment; **polyoxyalkylene** stabilizer magnetic pigmentIT Pigments
(magnetic, stabilization of, with **polyoxyalkylated siloxanes**)IT **Recording** apparatus
(magnetic tape, chromium dioxide magnetic pigments for, stabilization of)IT **Siloxanes** and Silicones, uses and miscellaneous
(**polyoxyalkylated**, stabilization by, of chromium dioxide

IT magnetic pigments)
IT 12018-01-8
 (pigments, magnetic stabilization of, by polyoxyalkylated
 siloxanes)
IT 9003-11-6D, ethers with **siloxanes** 25322-68-3D, ethers
 with **siloxanes** 25322-69-4D, ethers with
 siloxanes
 (stabilization by, of chromium dioxide magnetic pigment)